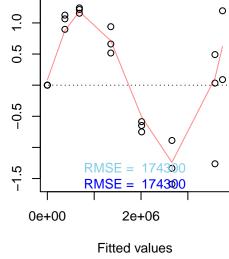


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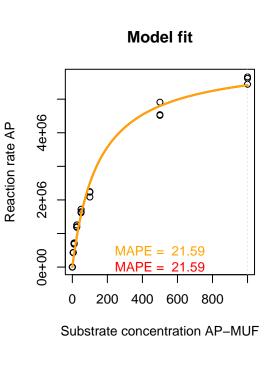
Substrate concentration AP–MUF

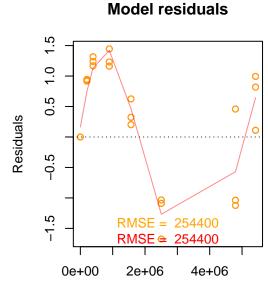
MAPE = 12.33

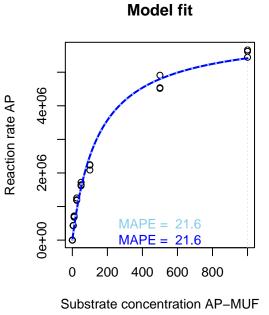
0e+00

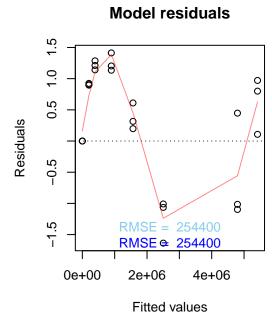




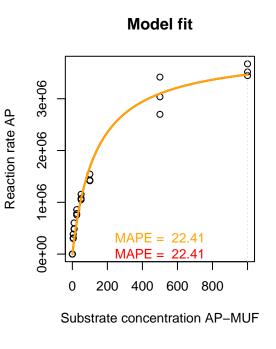


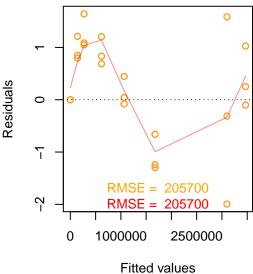








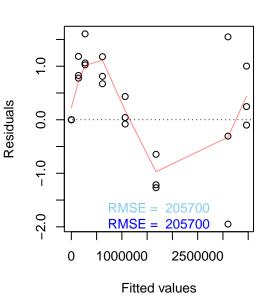


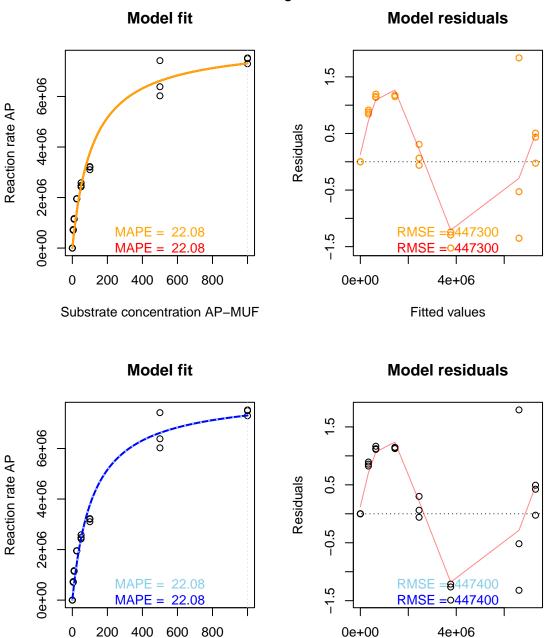




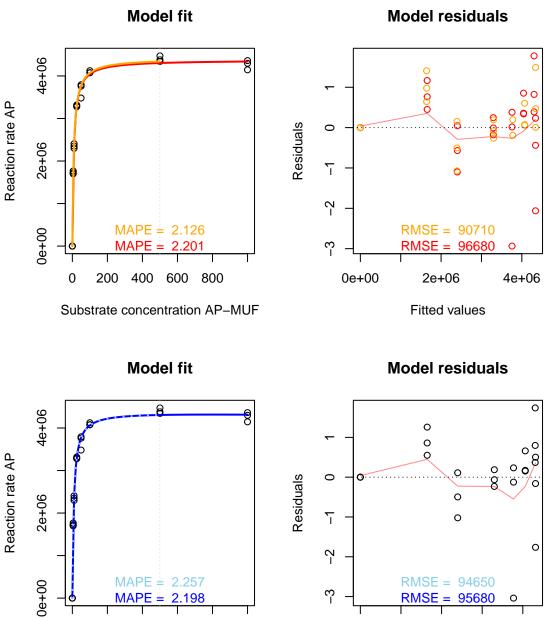
Reaction rate AP

Model residuals









0e+00

2e+06

Fitted values

4e+06

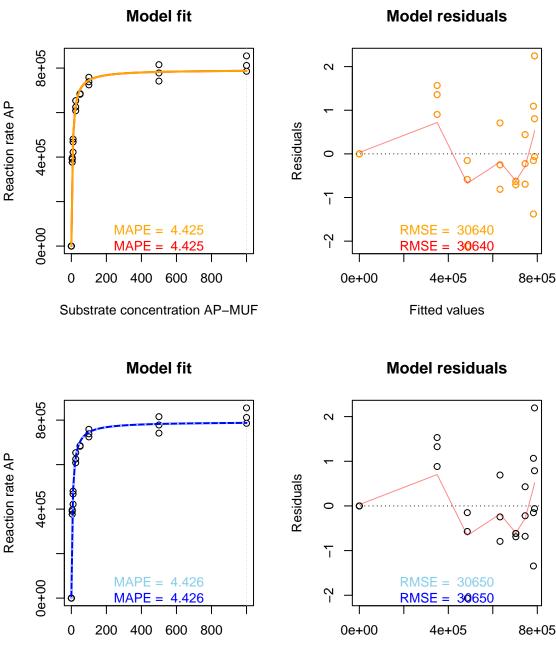
800

600

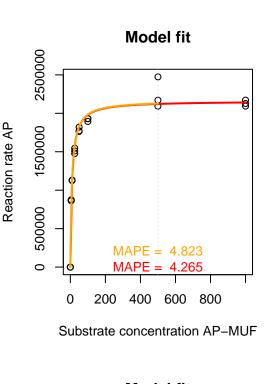
Substrate concentration AP-MUF

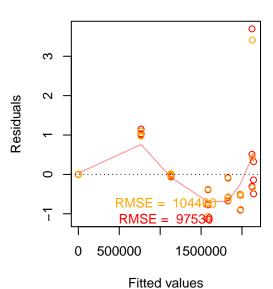
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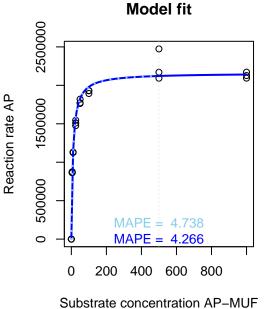
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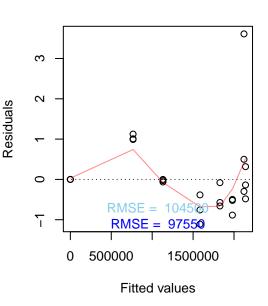




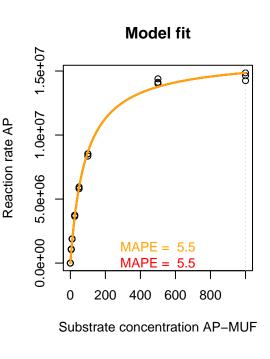




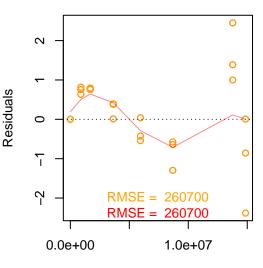
Model residuals



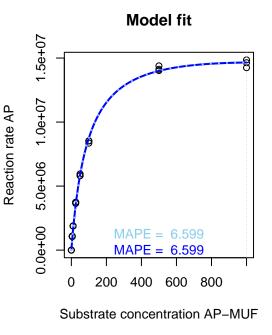


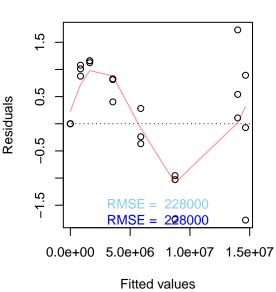


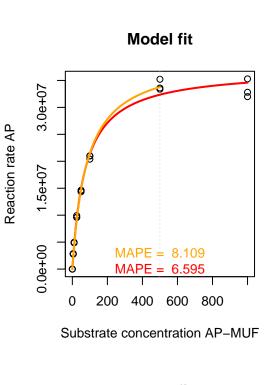


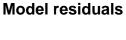


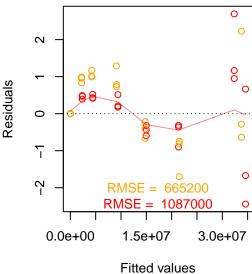
Fitted values

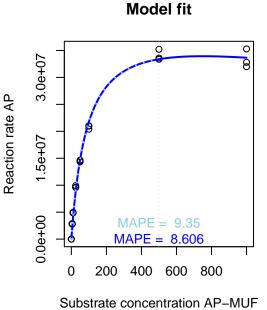




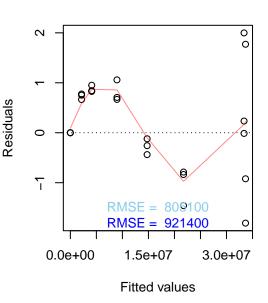


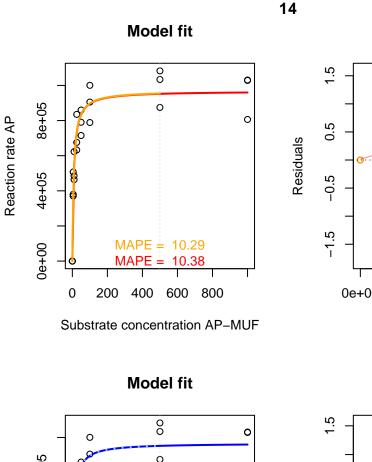


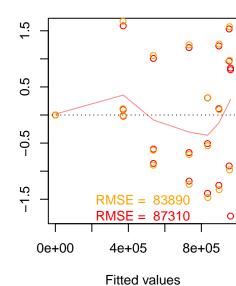


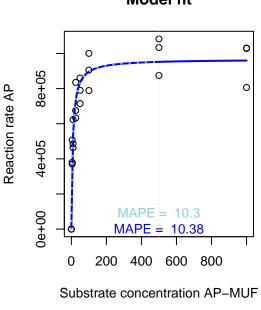


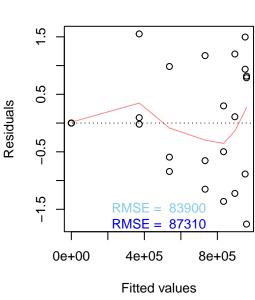


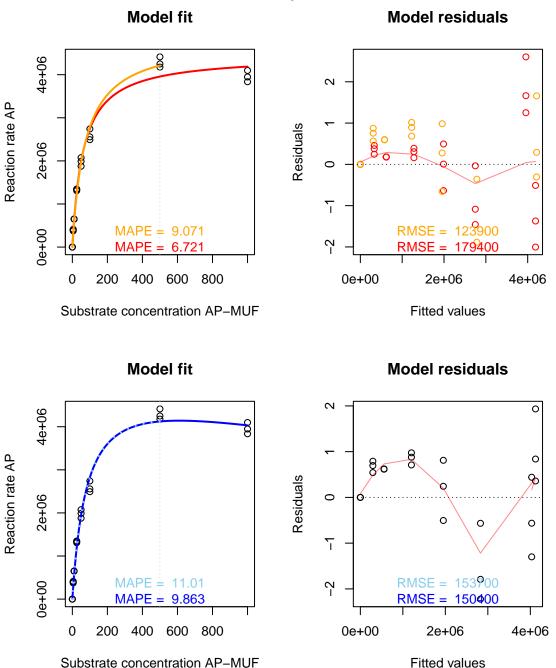


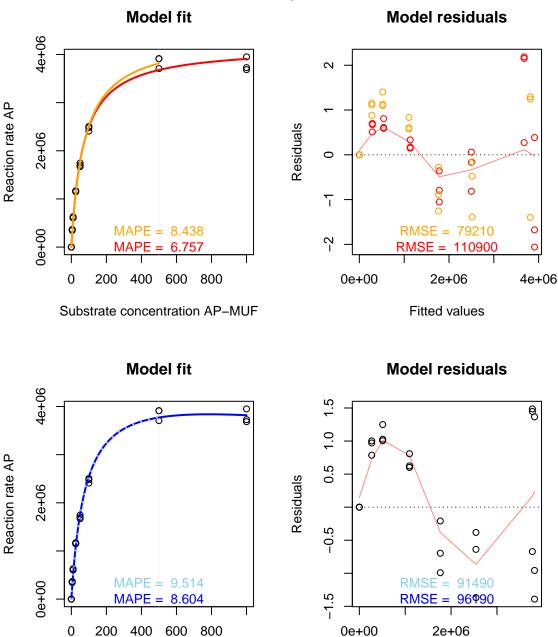




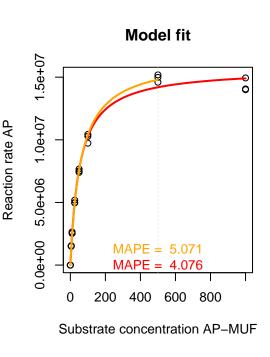


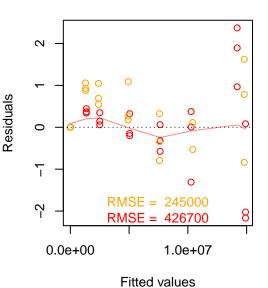


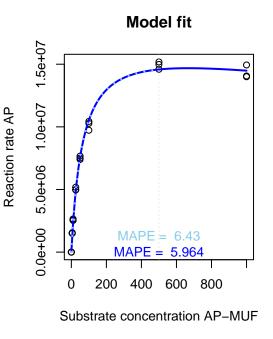




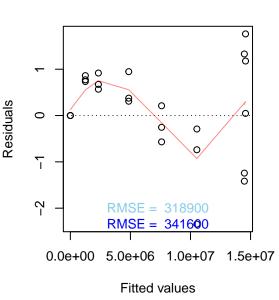


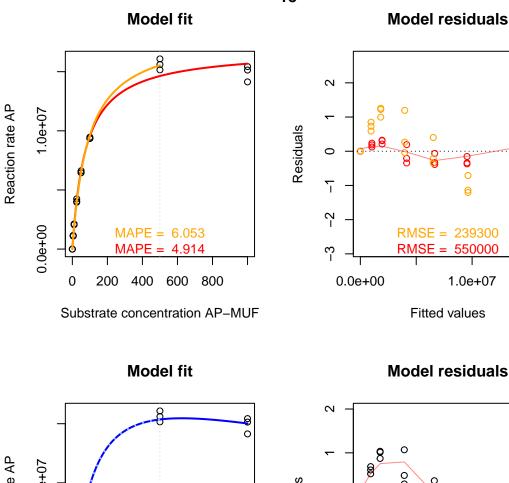


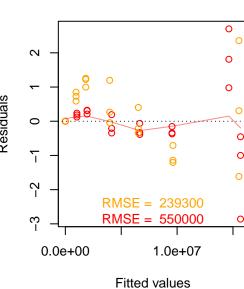


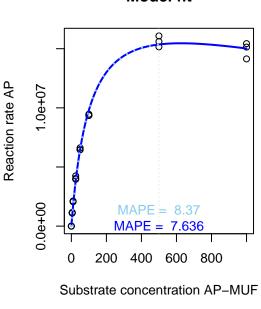


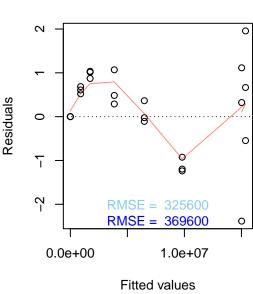
Model residuals

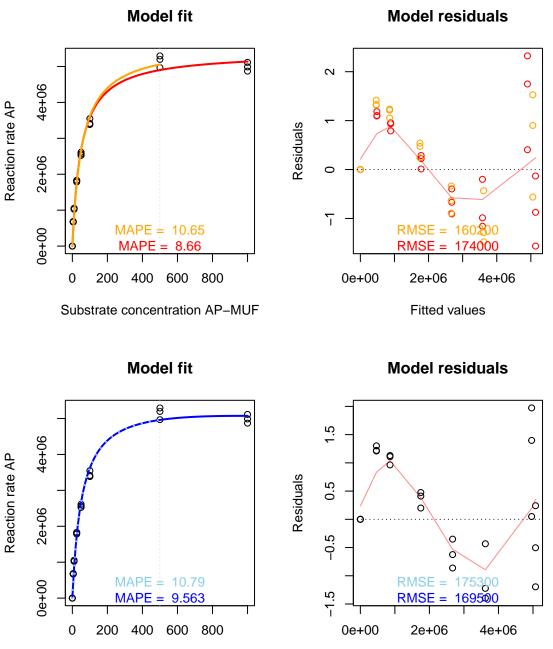




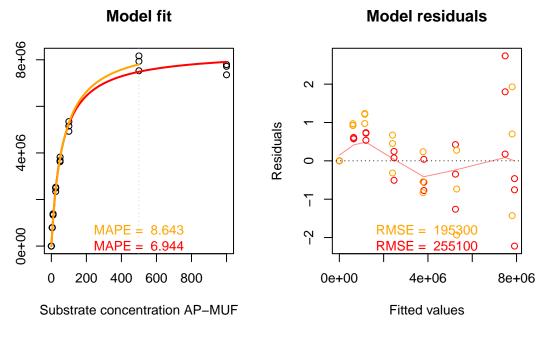


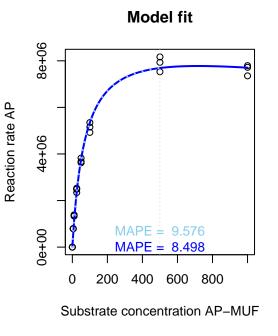




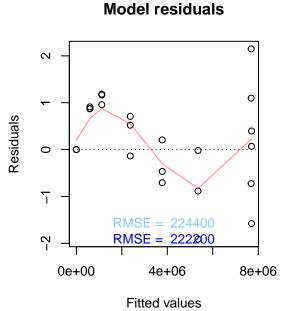


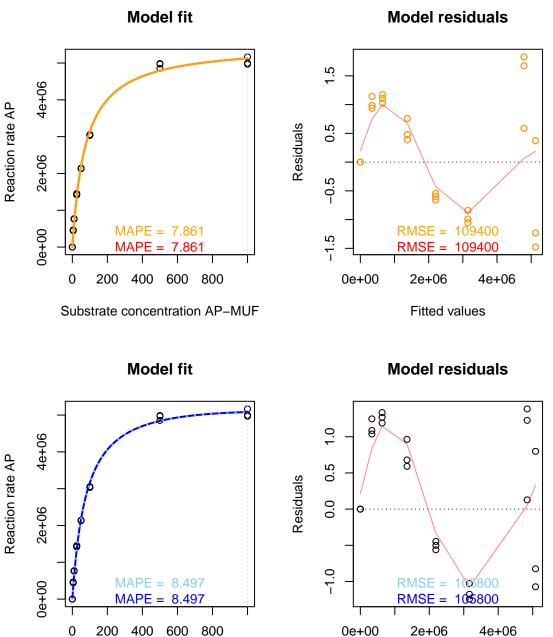




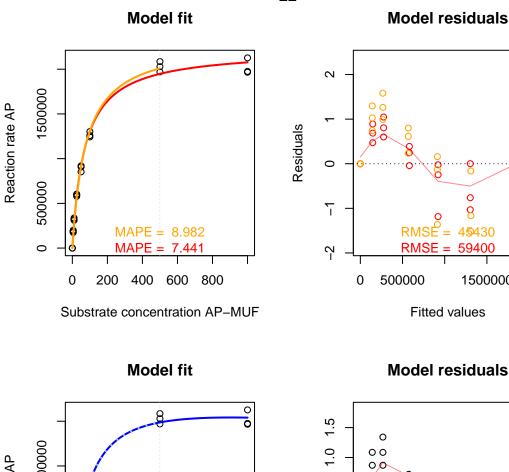


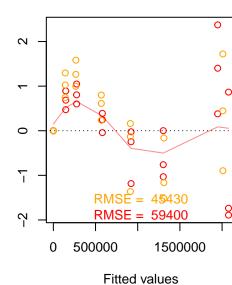
Reaction rate AP

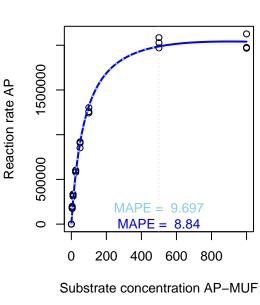


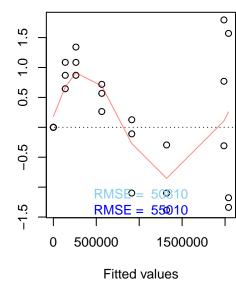


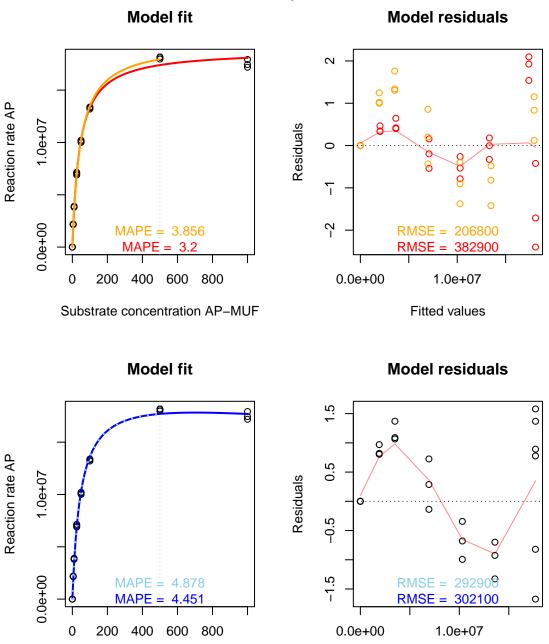
Residuals



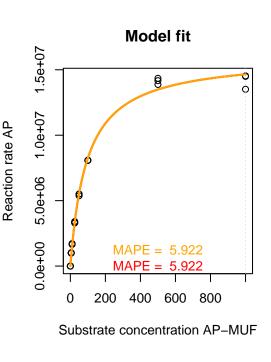


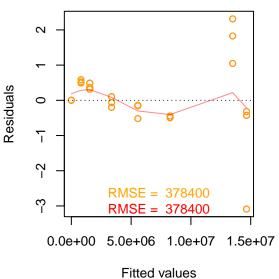


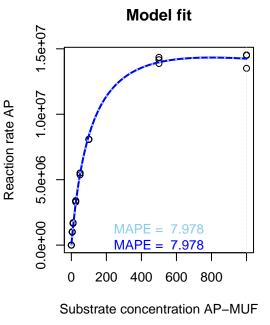




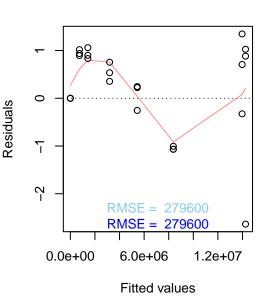




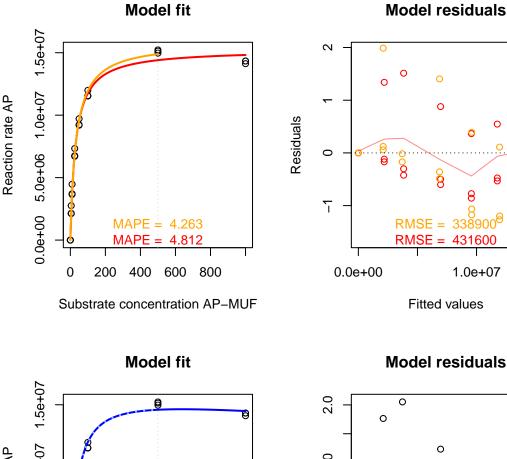




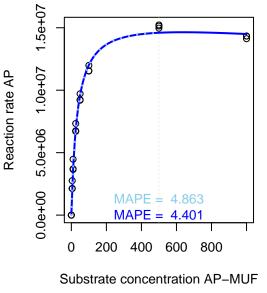
Model residuals

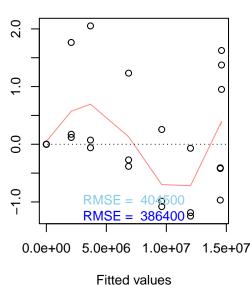


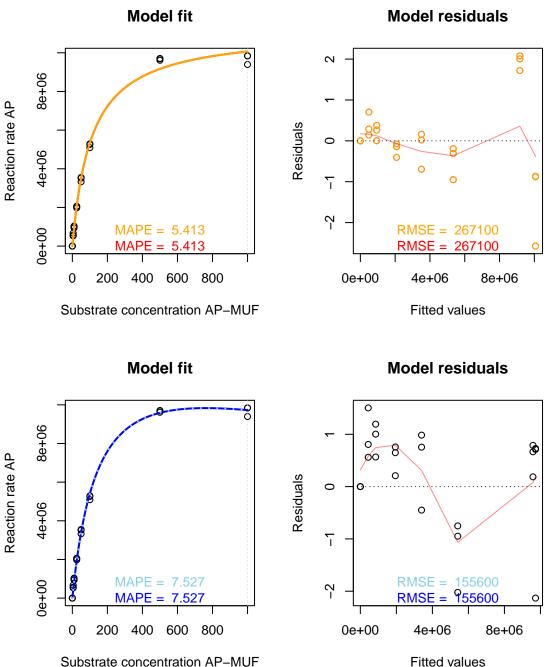


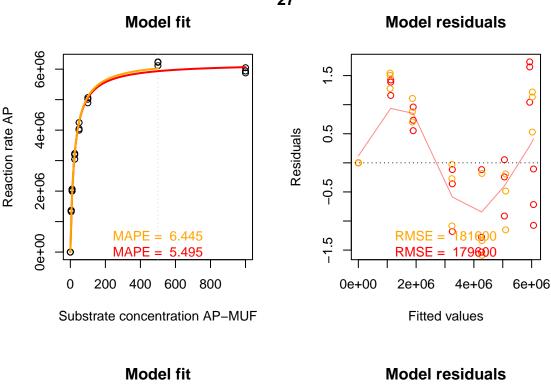


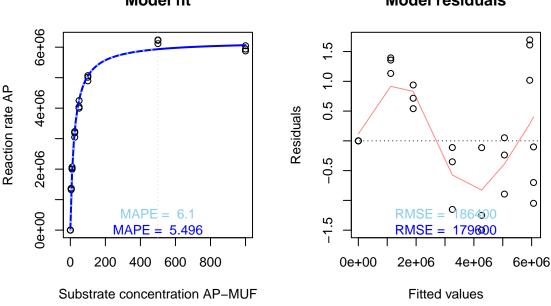
Residuals

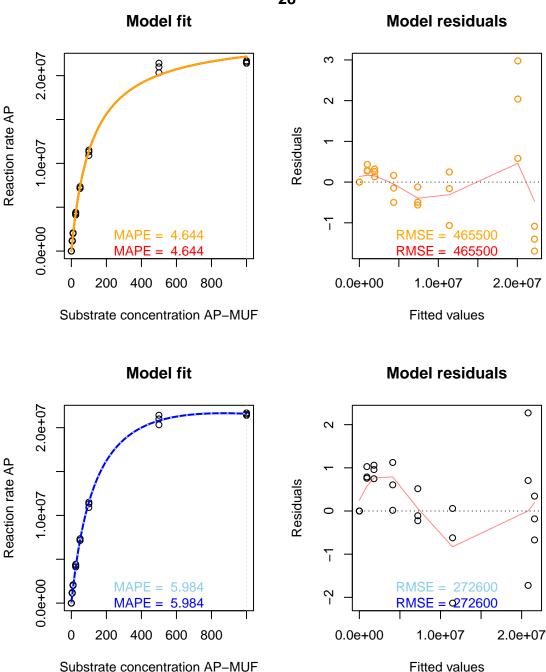


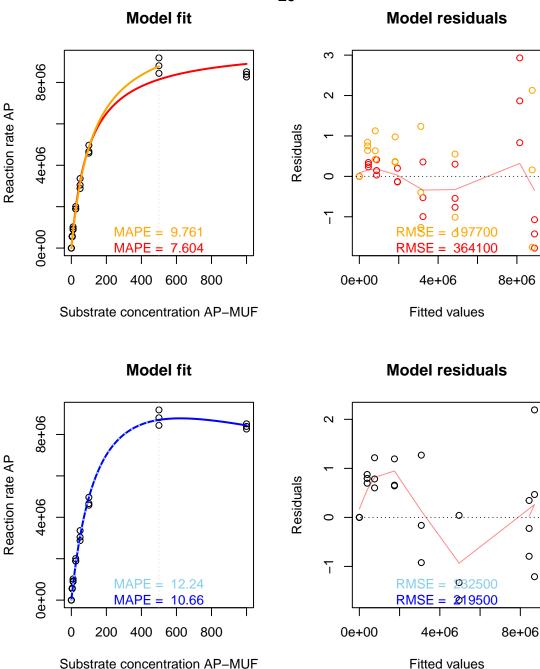


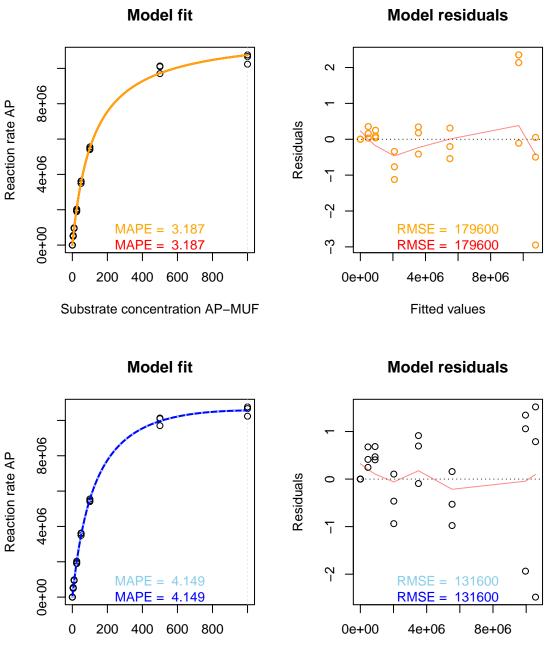


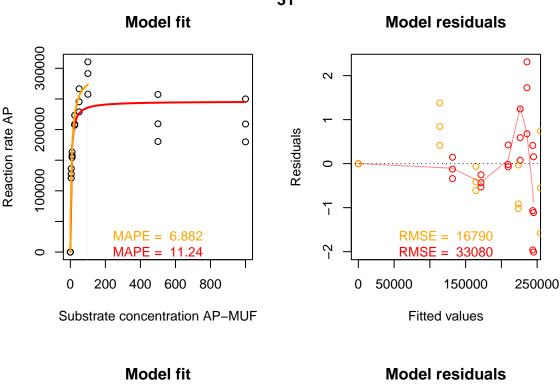


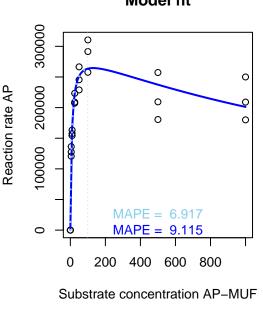


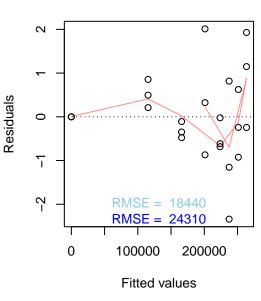










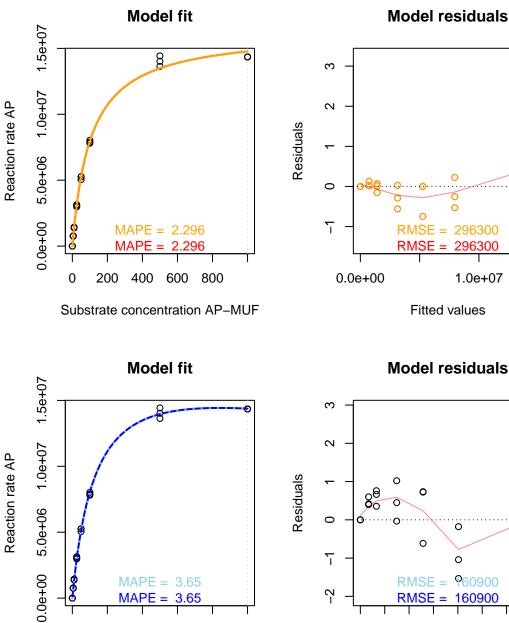


0

O

0

1.2e+07



0

200

400

600

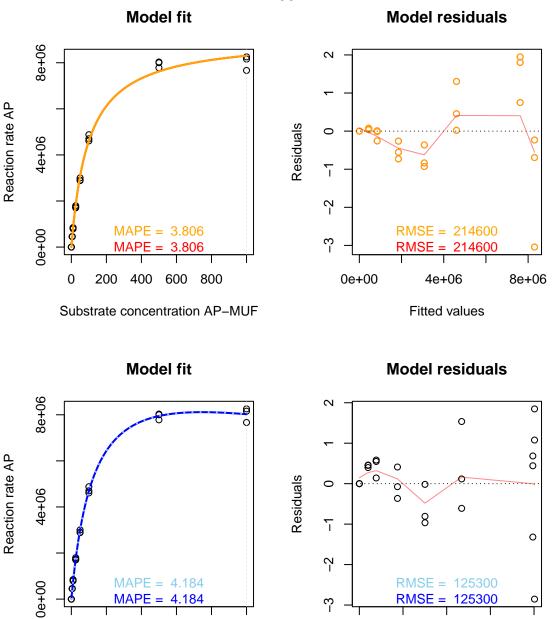
Substrate concentration AP-MUF

800

0.0e+00

6.0e+06

Fitted values



0e+00

4e+06

Fitted values

8e+06

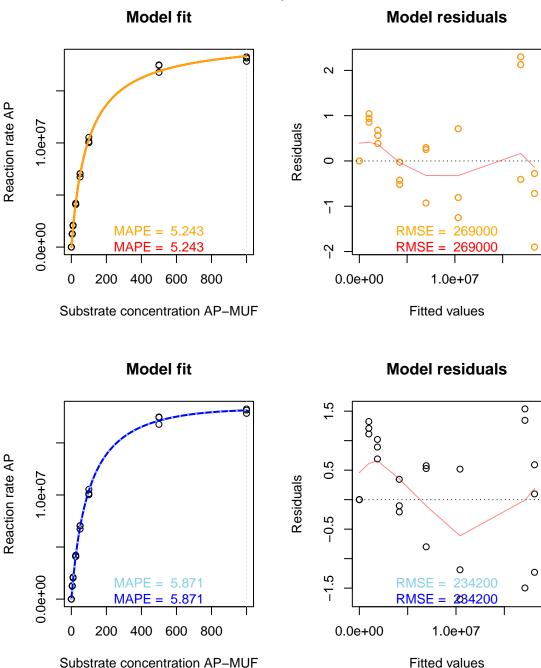
200

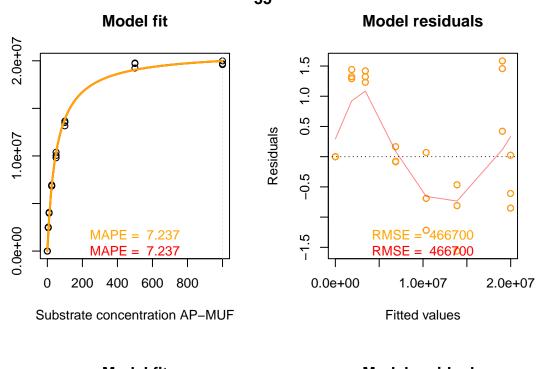
400

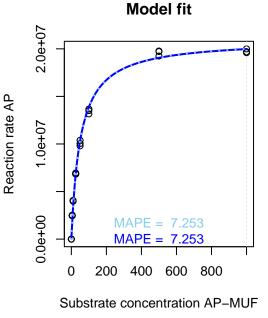
600

Substrate concentration AP-MUF

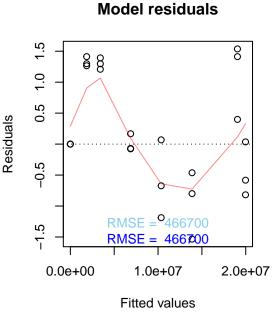
800

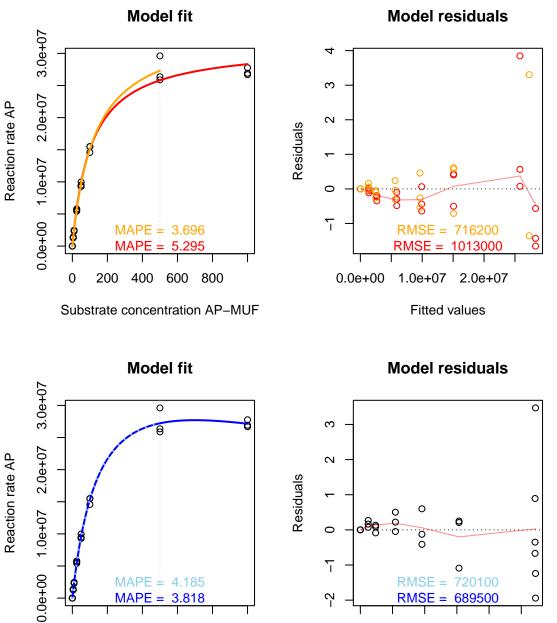






Reaction rate AP





0.0e + 00

1.0e+07

Fitted values

2.0e+07

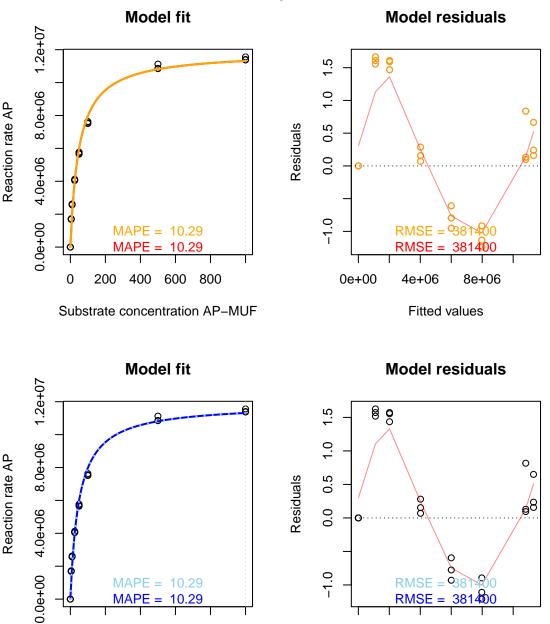
Substrate concentration AP-MUF

600

800

400

0



0e+00

4e+06

Fitted values

8e+06

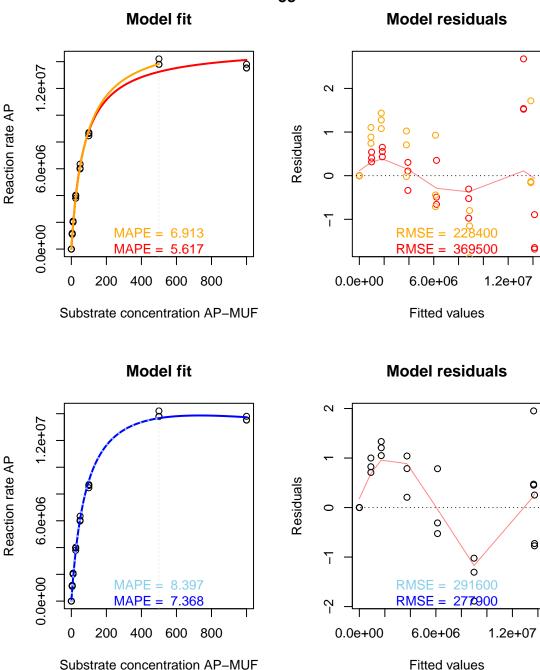
200

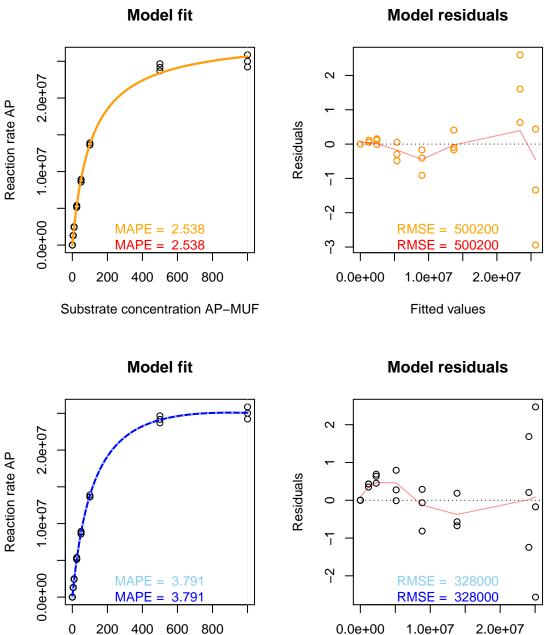
0

400

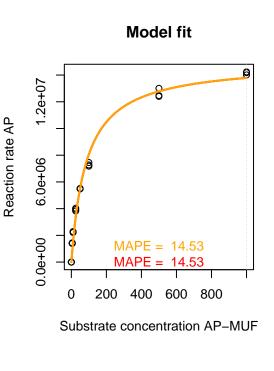
800

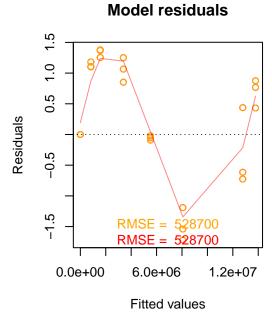
600

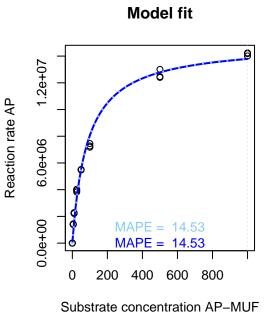


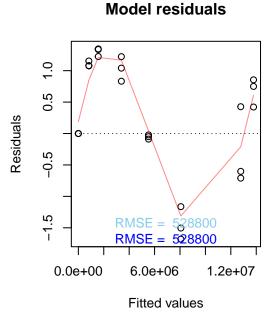


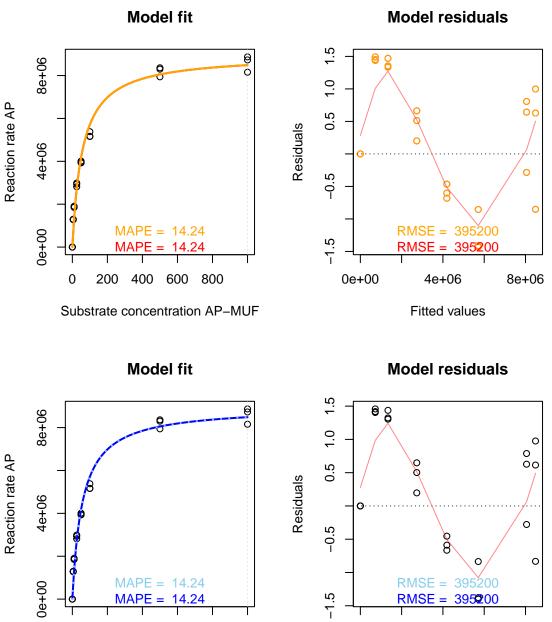












200

400

600

Substrate concentration AP-MUF

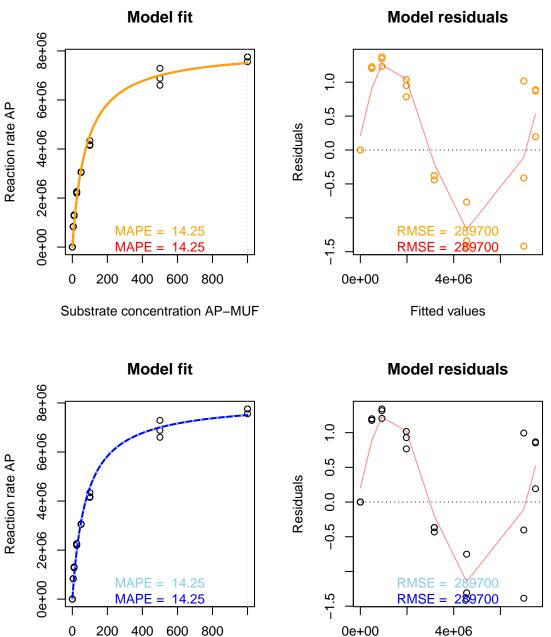
800

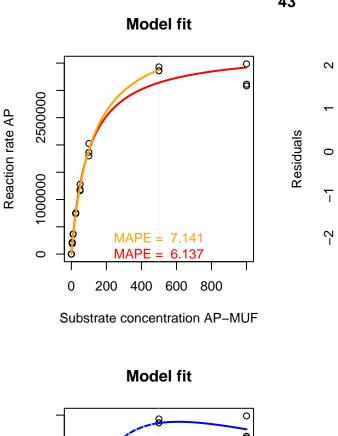
0e+00

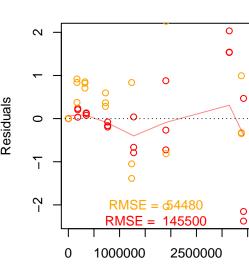
4e+06

Fitted values

8e+06

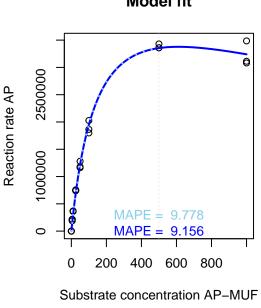


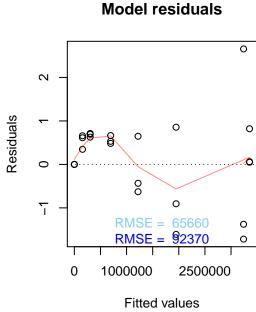




Model residuals

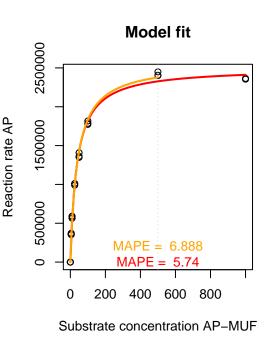
Fitted values



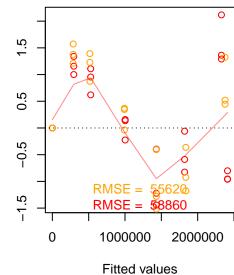




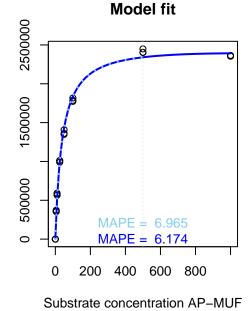
Residuals



Model residuals

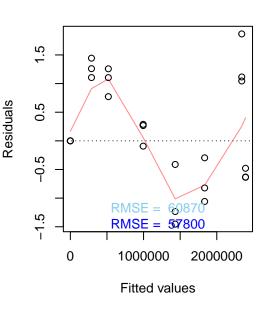


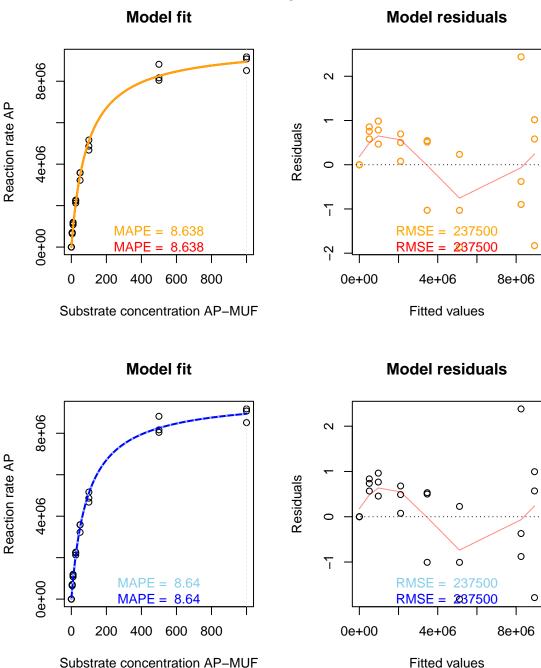


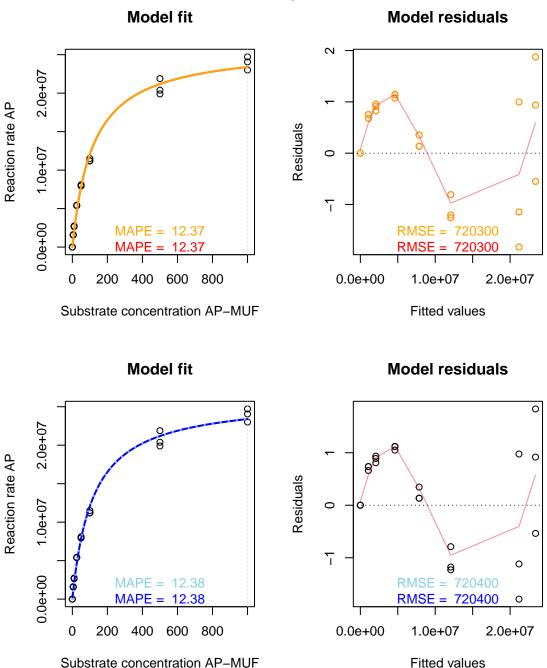


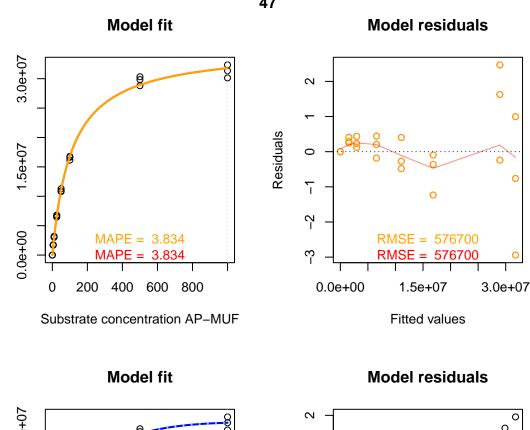
Reaction rate AP

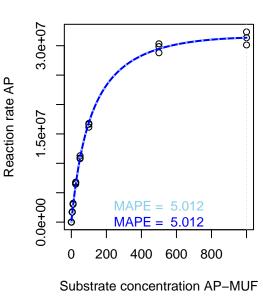
Model residuals



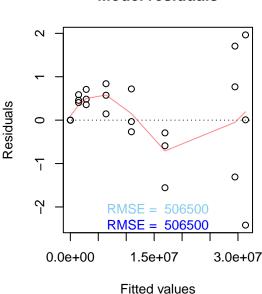




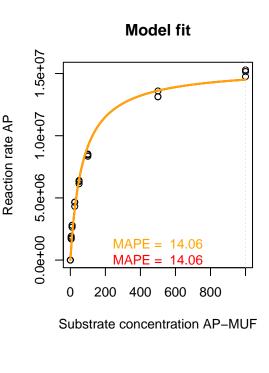


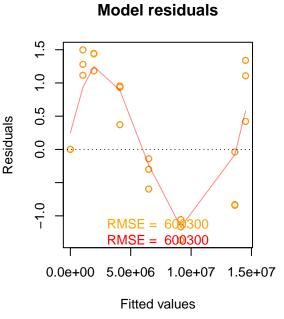


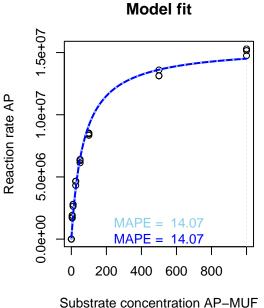
Reaction rate AP

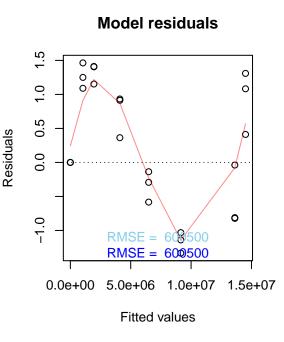




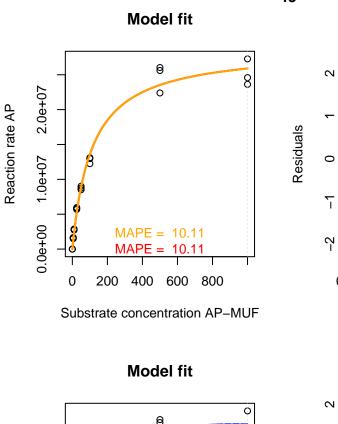


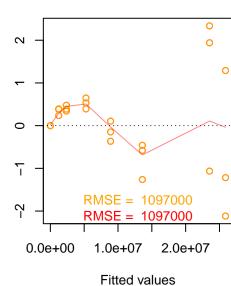




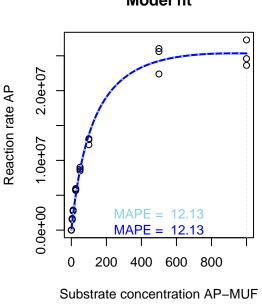


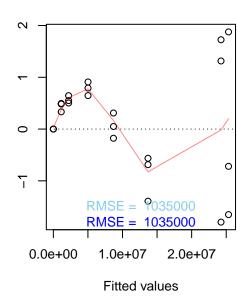
Residuals





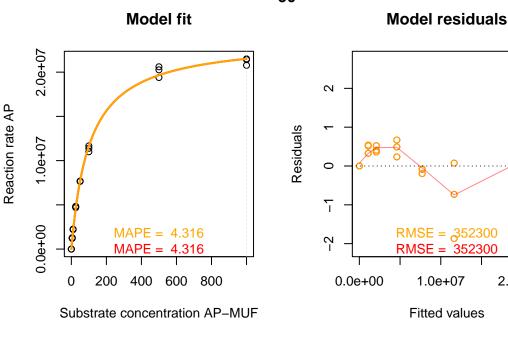
Model residuals

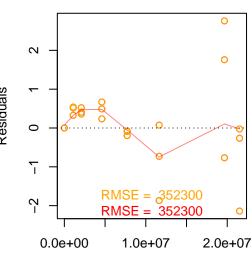


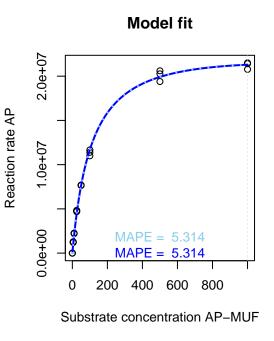


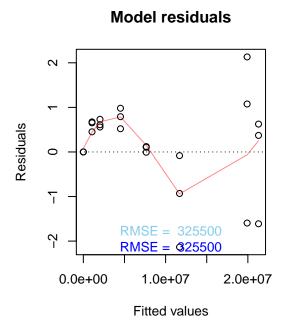
Model residuals



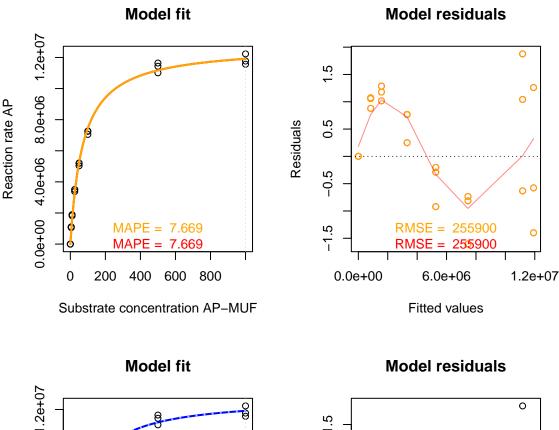




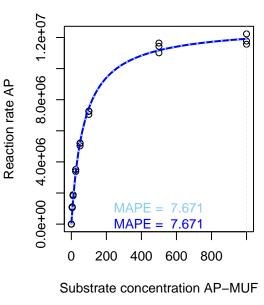


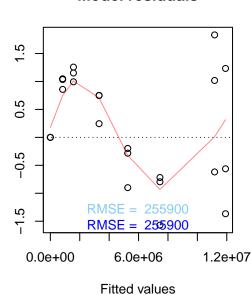


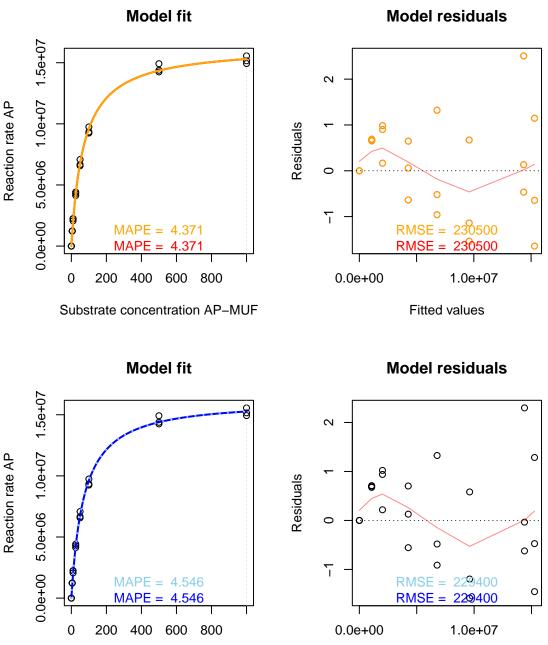


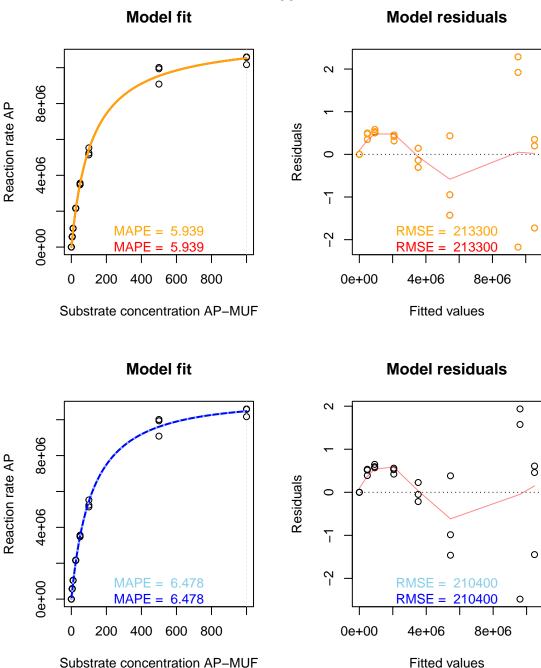


Residuals

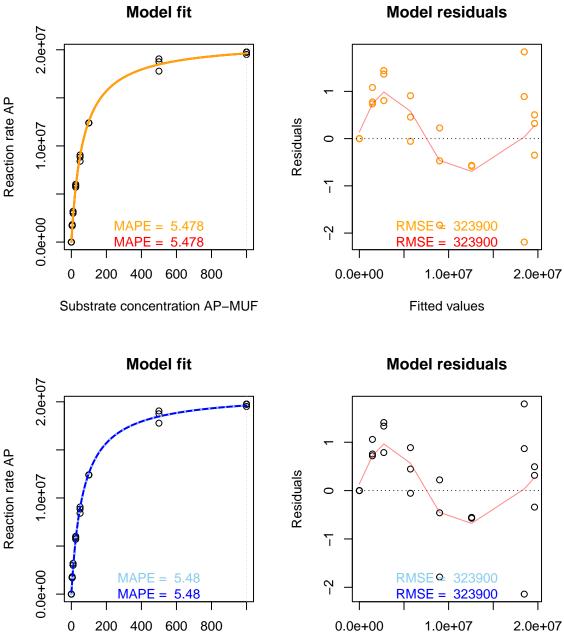


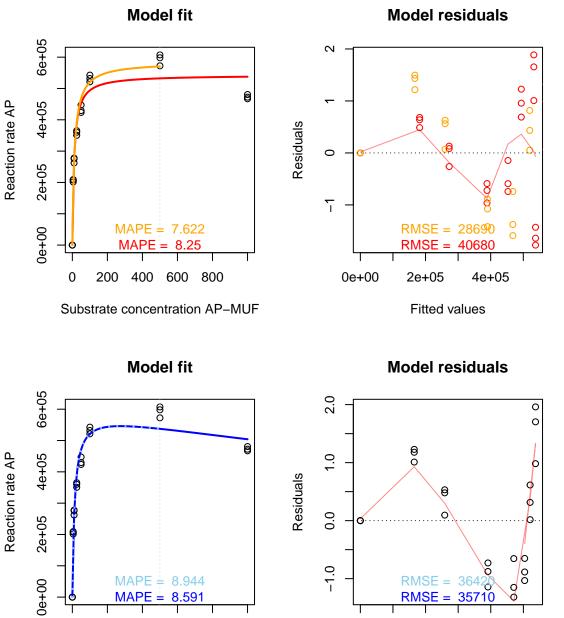












200

400

600

Substrate concentration AP-MUF

800

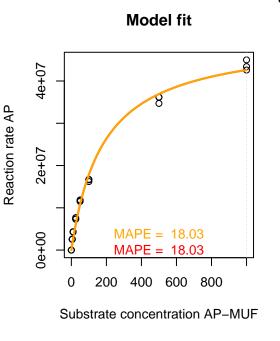
0e+00

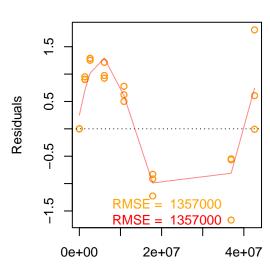
2e+05

Fitted values

4e+05

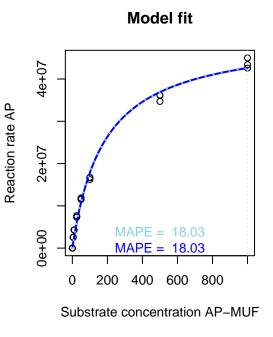


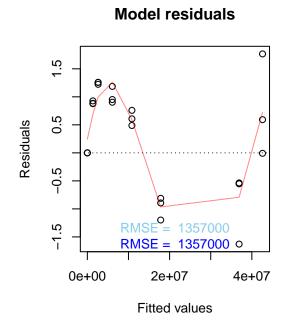


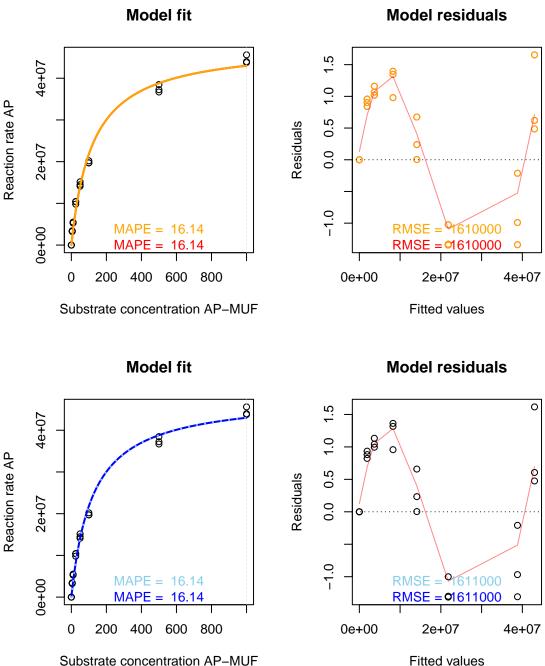


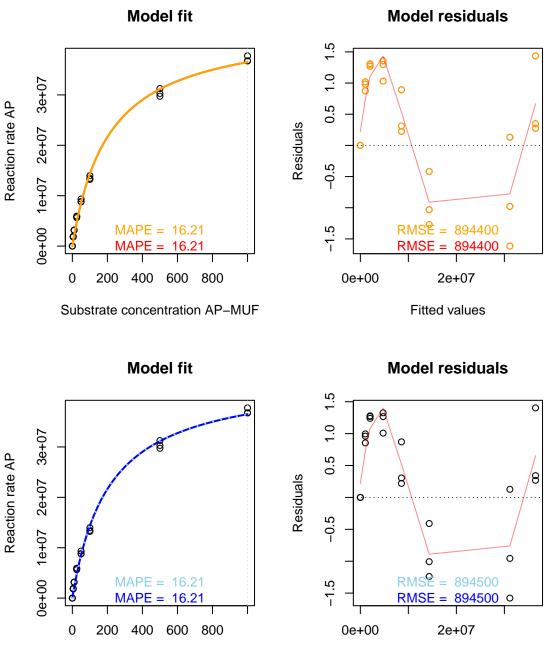
Model residuals

Fitted values

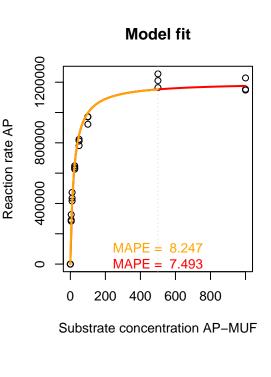


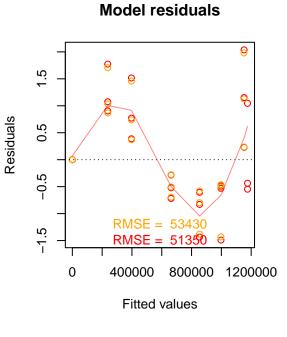


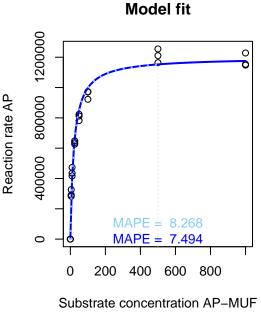


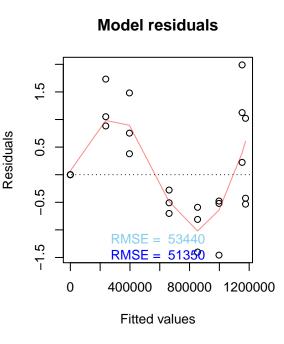


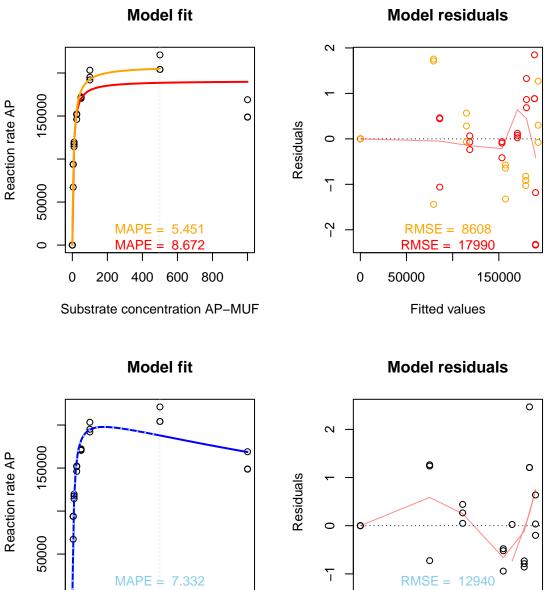






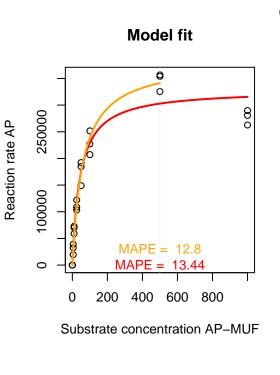


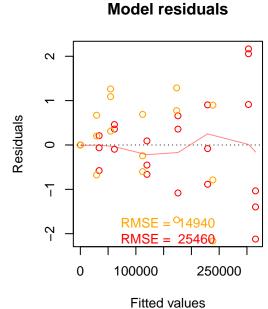


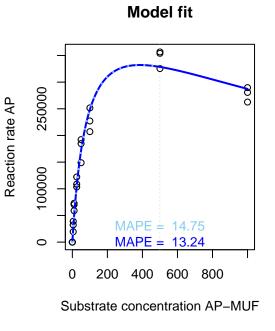


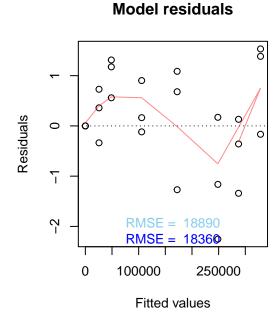
Substrate concentration AP-MUF

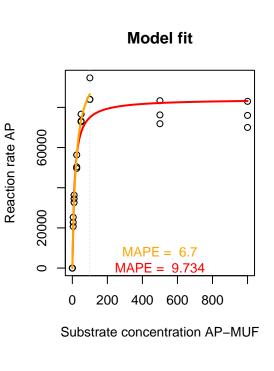
Fitted values

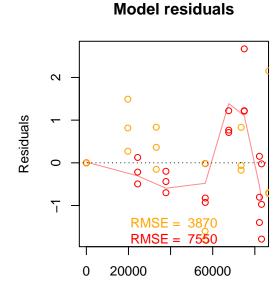


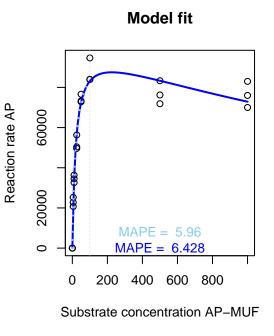


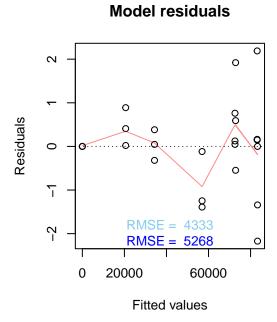


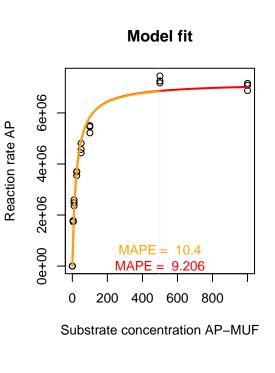


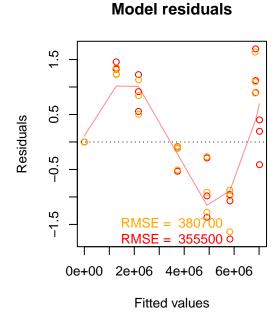


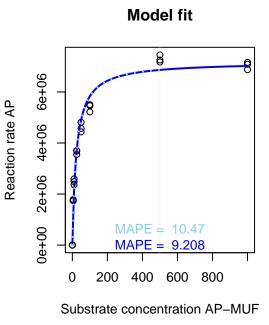


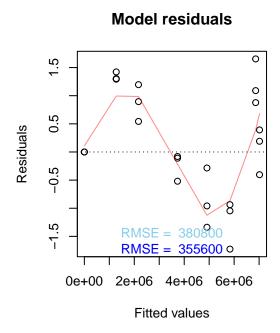


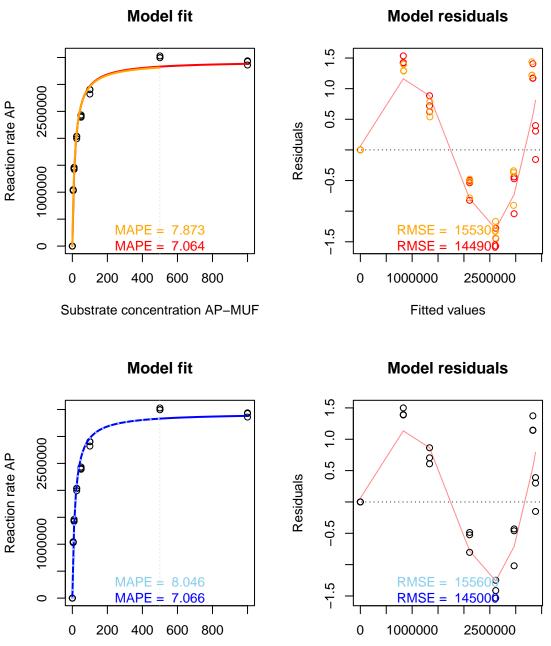




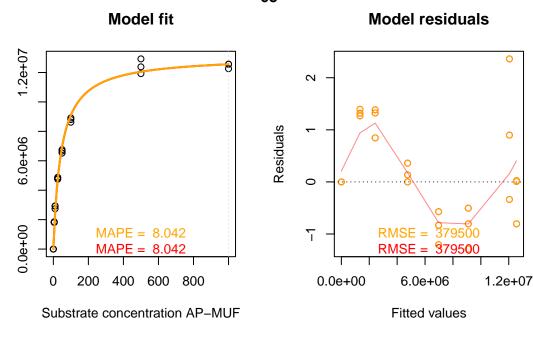


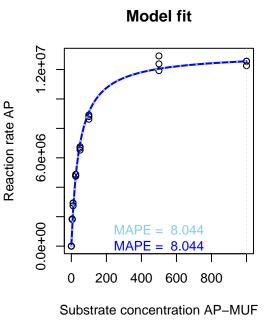




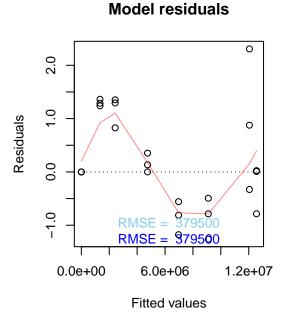


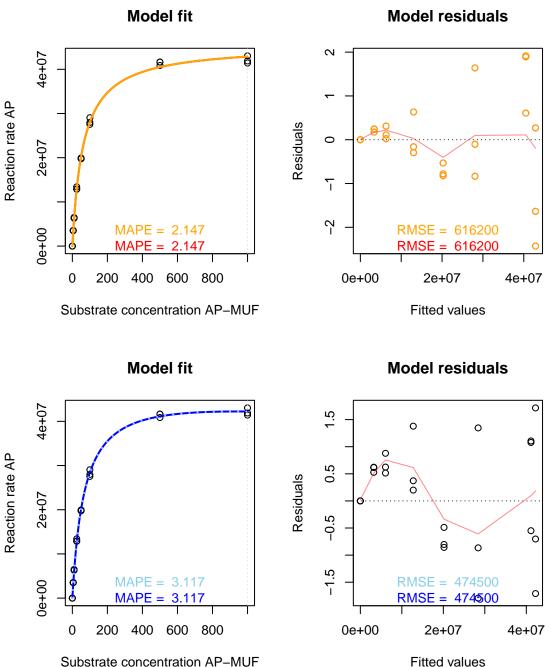


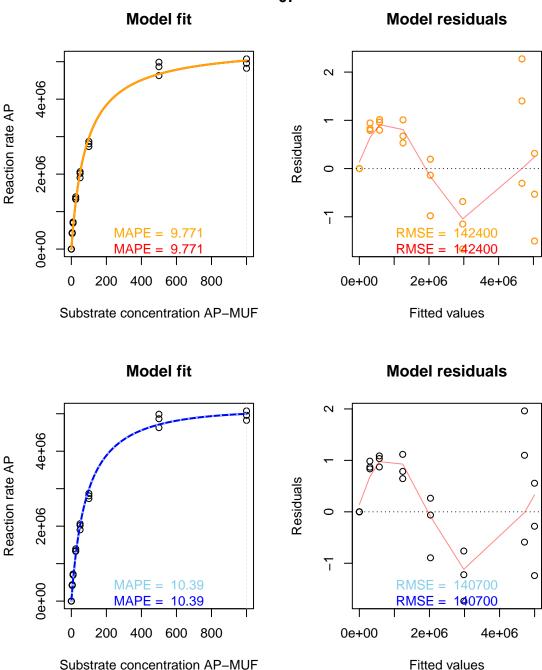


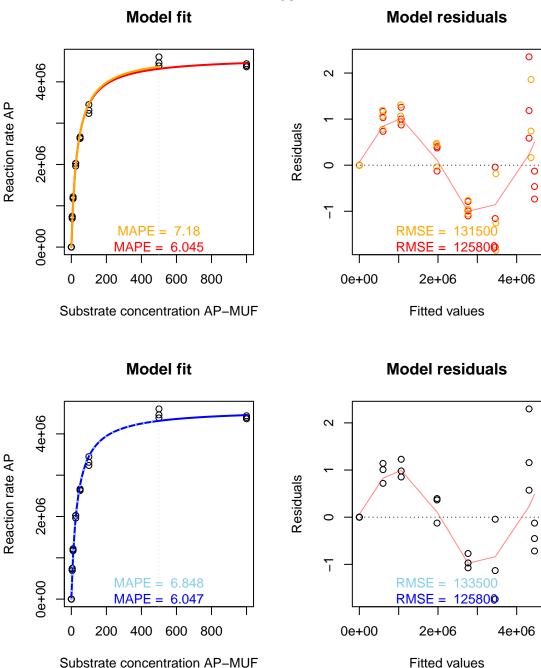


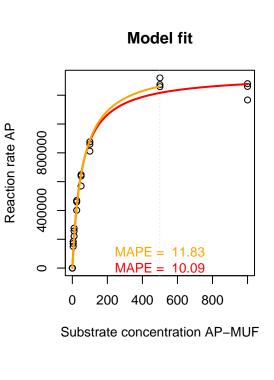
Reaction rate AP

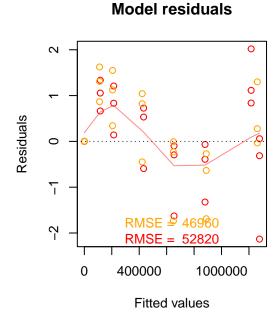


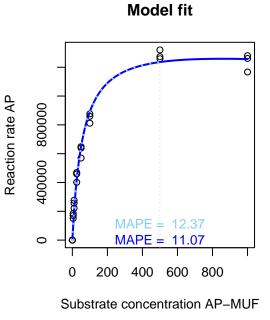


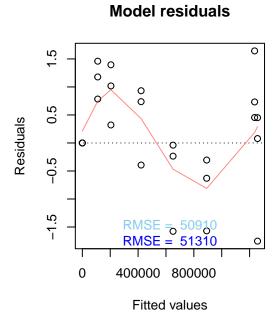




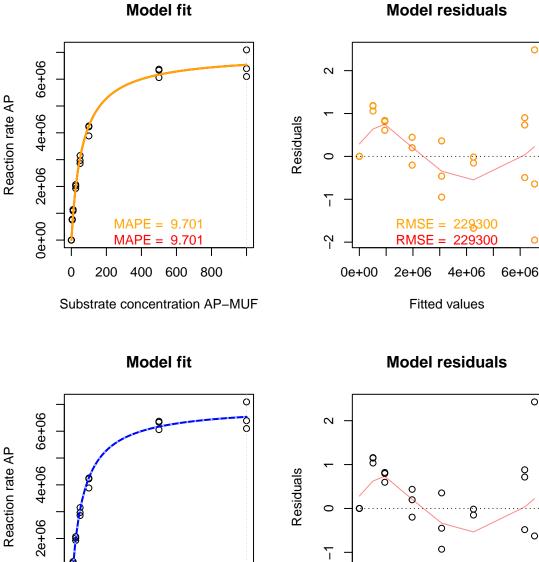








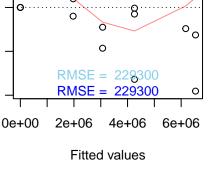


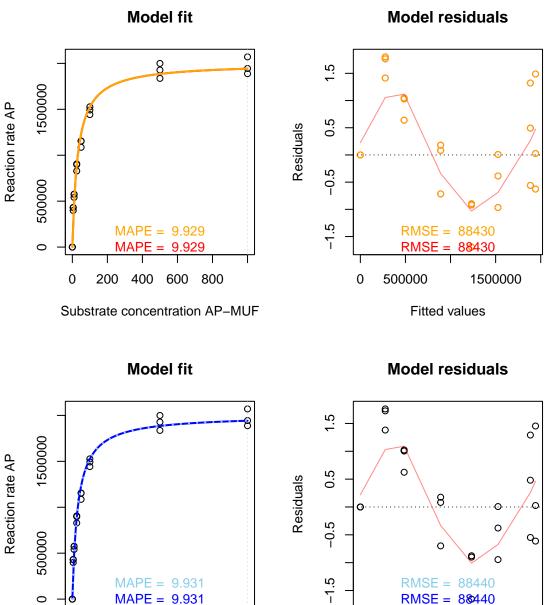


Substrate concentration AP-MUF

MAPE = 9.703

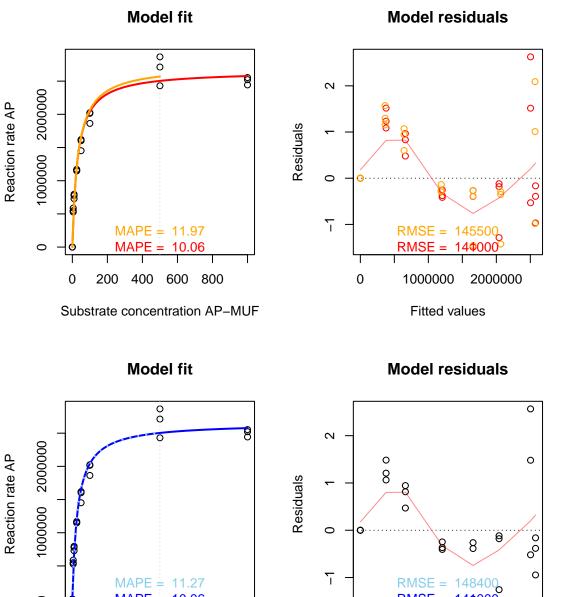
0e+00





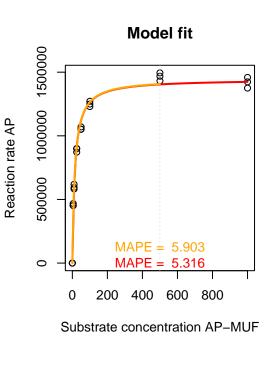
Substrate concentration AP-MUF

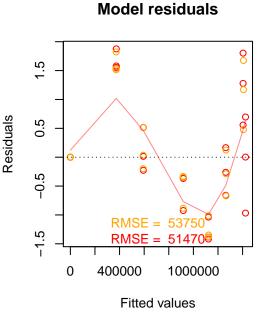
Fitted values

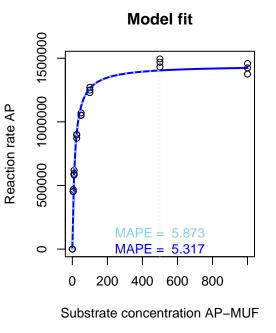


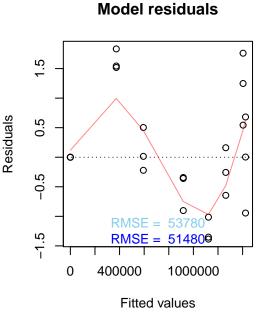
Fitted values

Substrate concentration AP-MUF

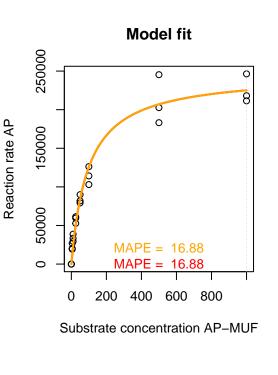




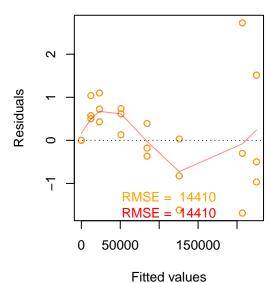


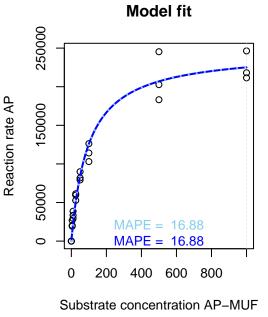




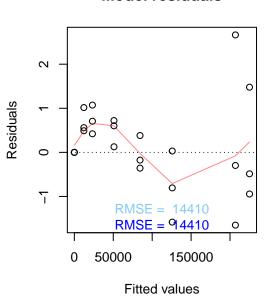


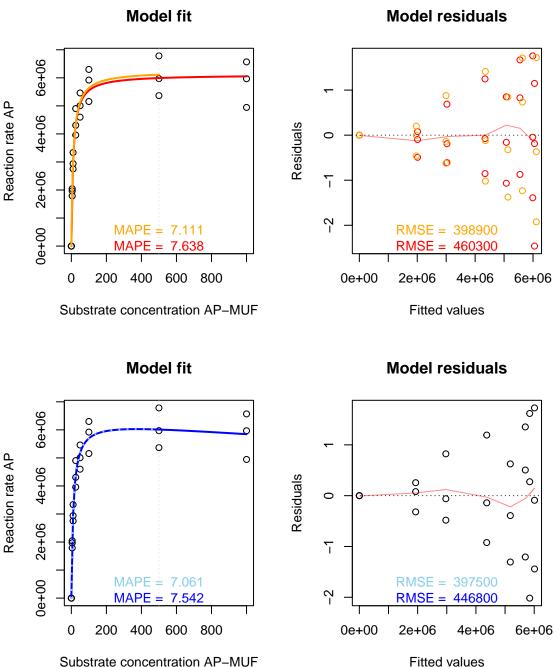
Model residuals



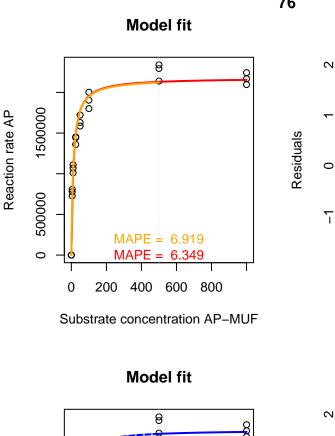


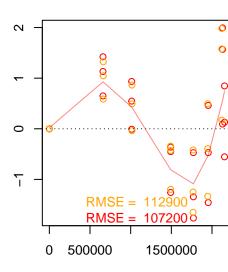
Model residuals





Residuals

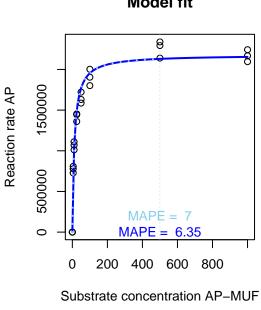


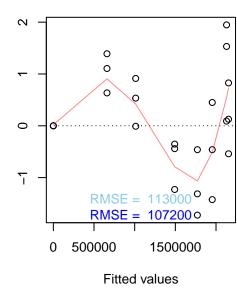


Fitted values

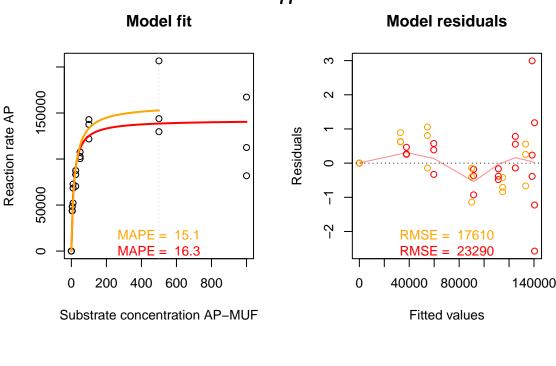
Model residuals

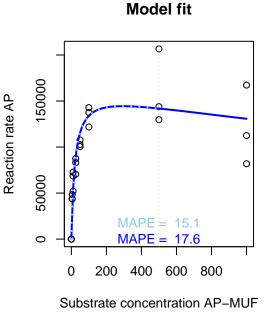
Model residuals

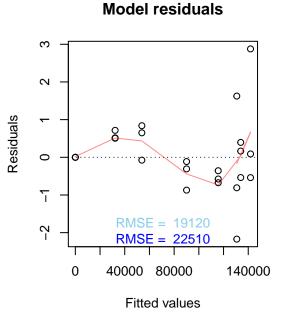




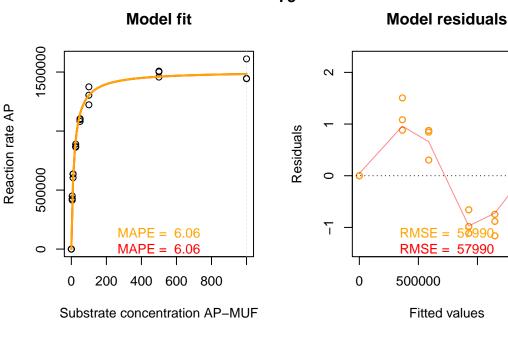


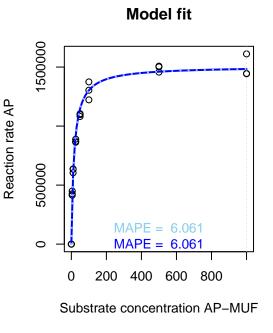




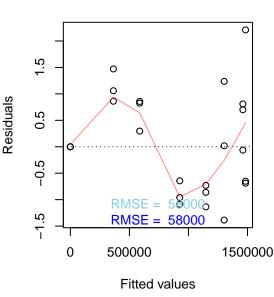


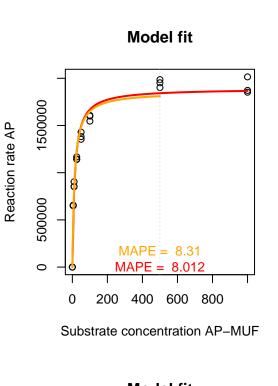


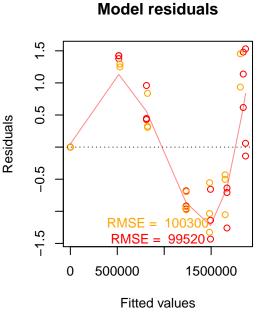


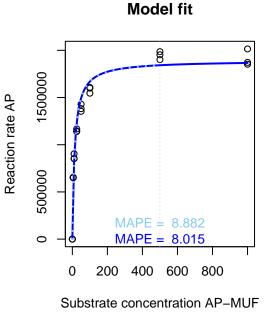


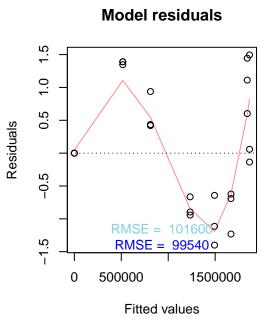


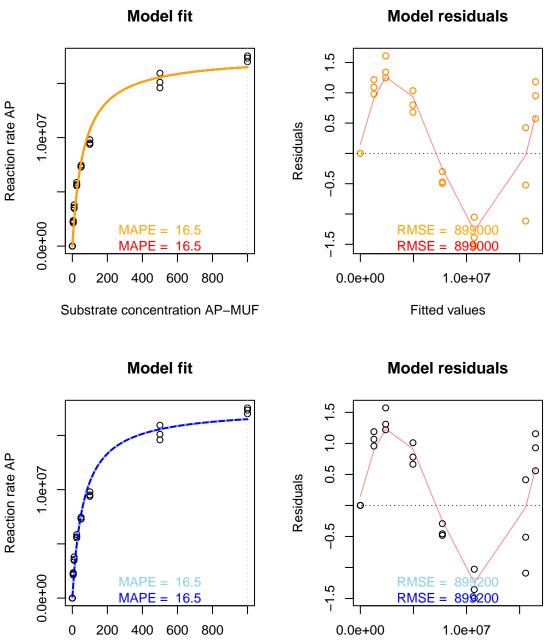




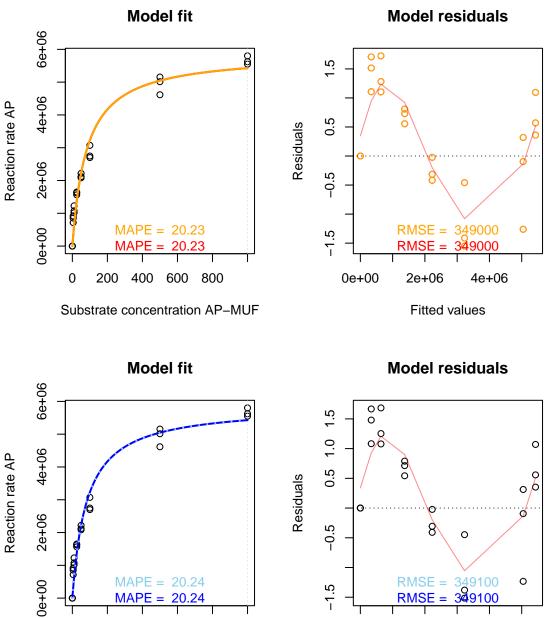












600

Substrate concentration AP-MUF

0

200

400

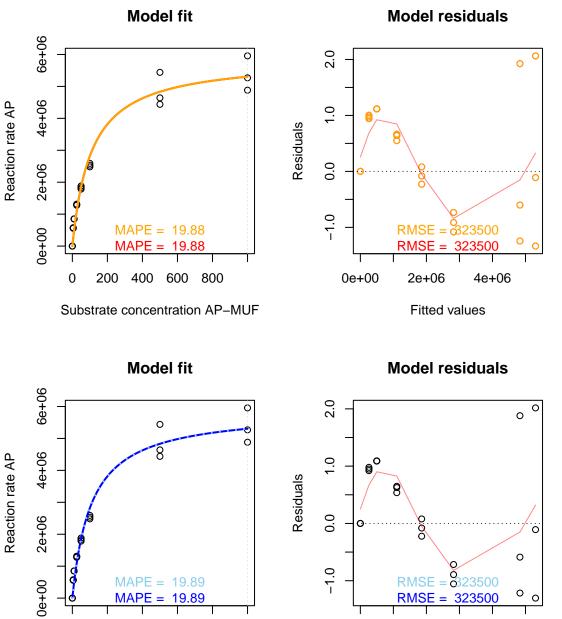
0e+00

2e+06

Fitted values

4e+06





0e+00

2e+06

Fitted values

4e+06

800

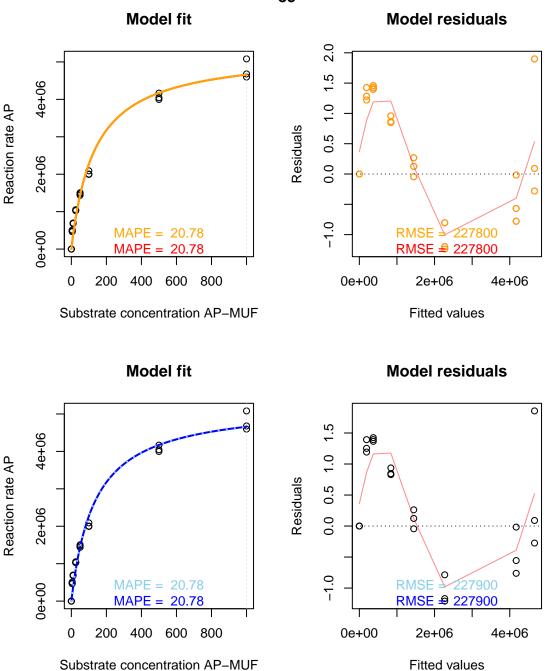
600

Substrate concentration AP-MUF

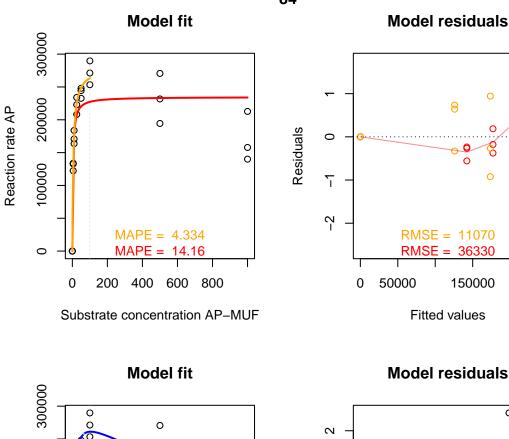
0

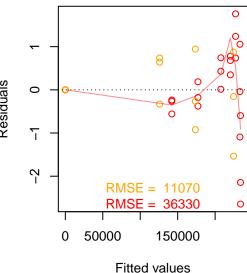
200

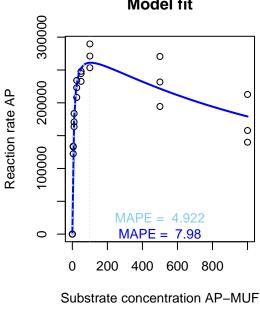
400

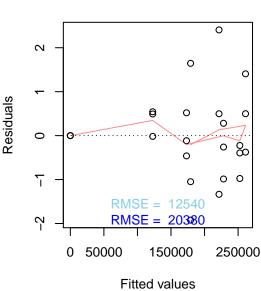


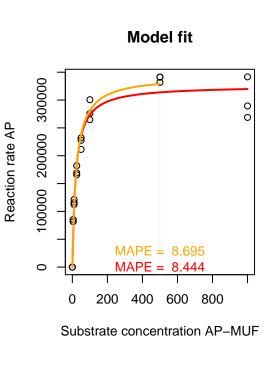


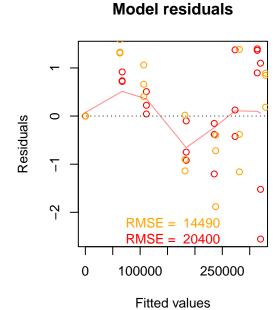


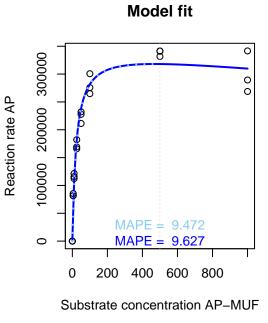


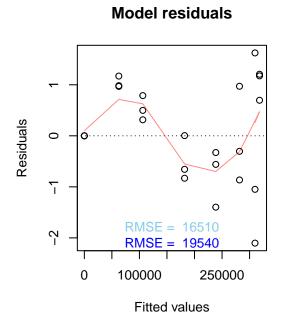


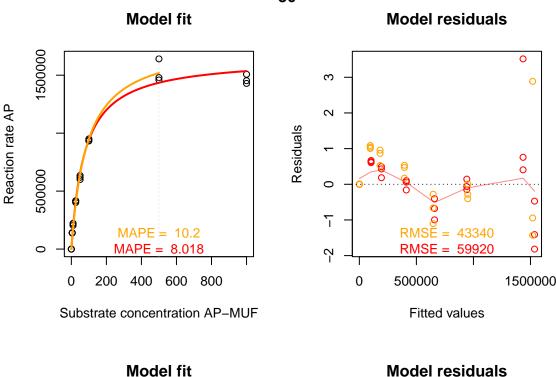


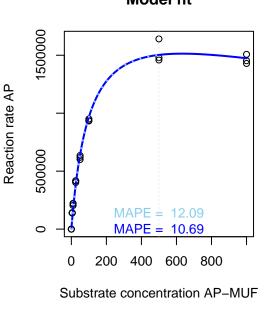


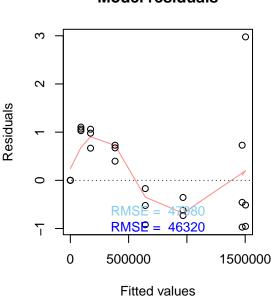


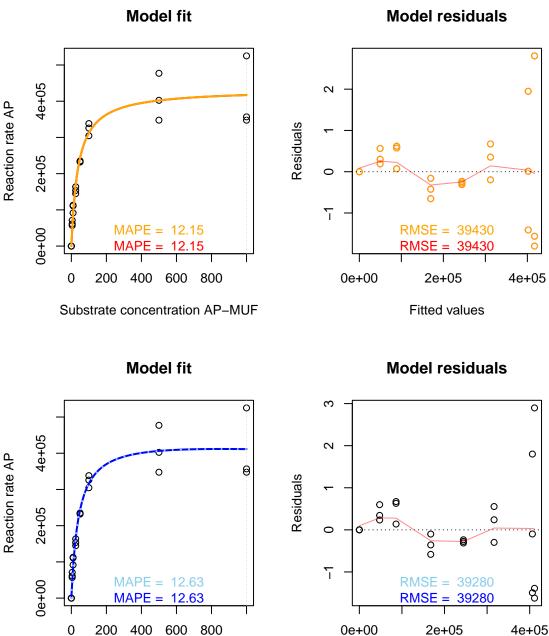


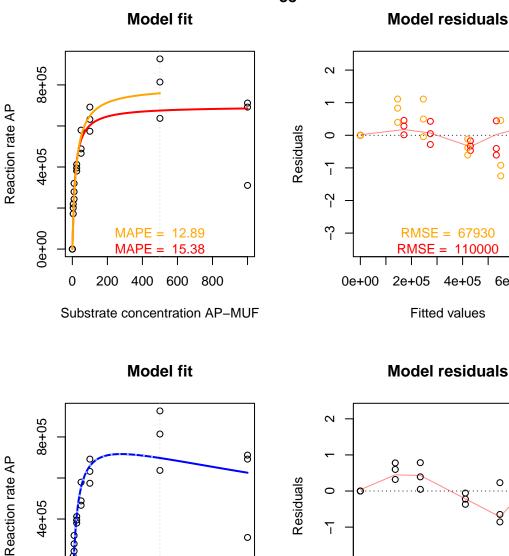


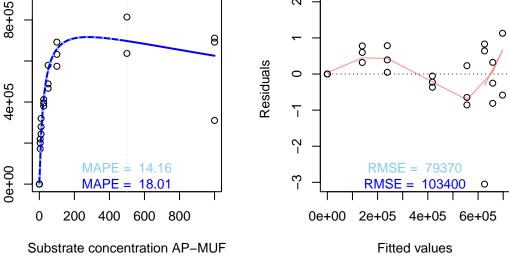








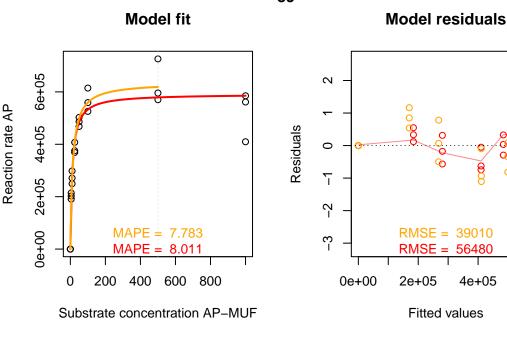


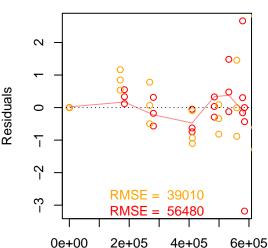


6e+05

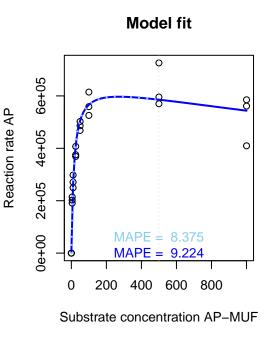
4e + 05

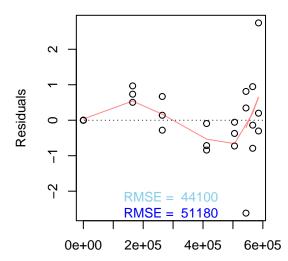




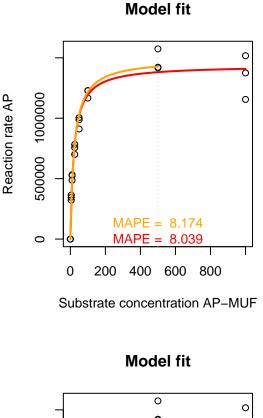


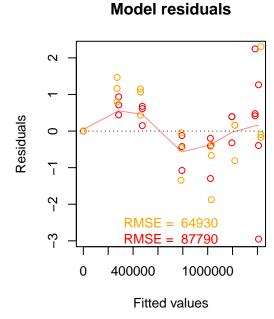
Model residuals

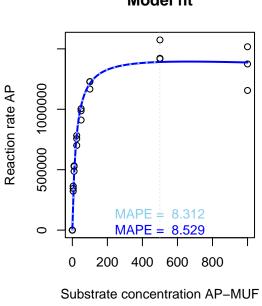


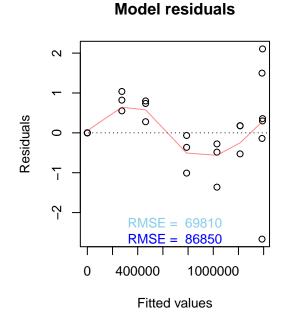


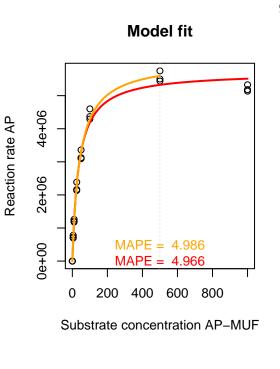
Fitted values

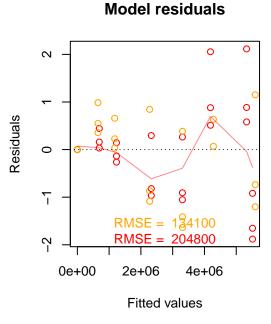


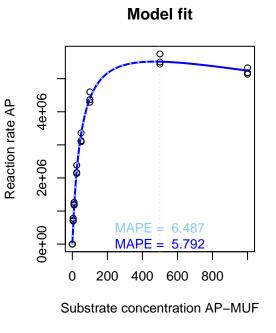


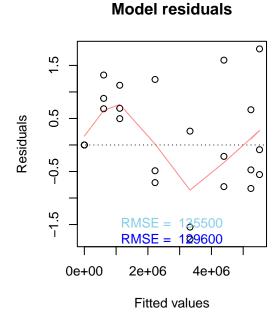




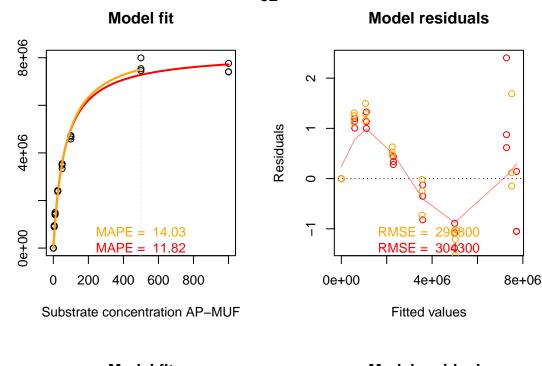


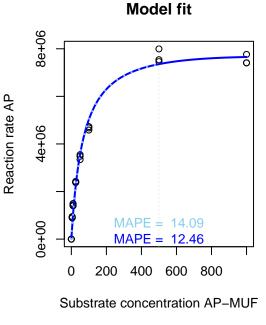




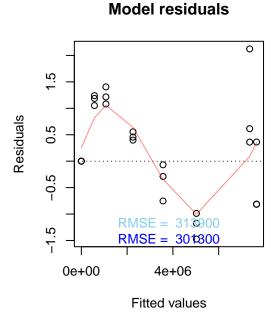




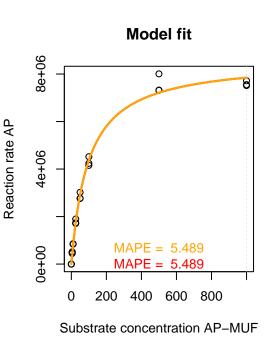


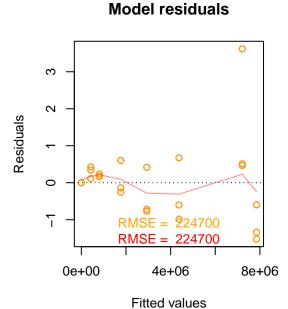


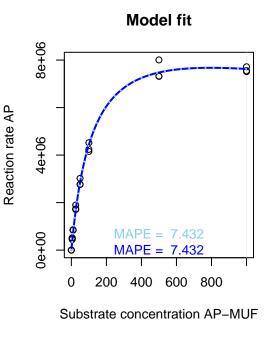
Reaction rate AP

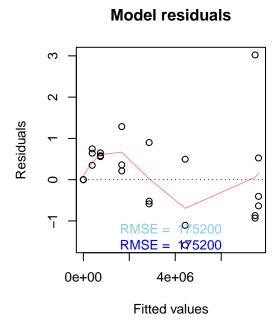




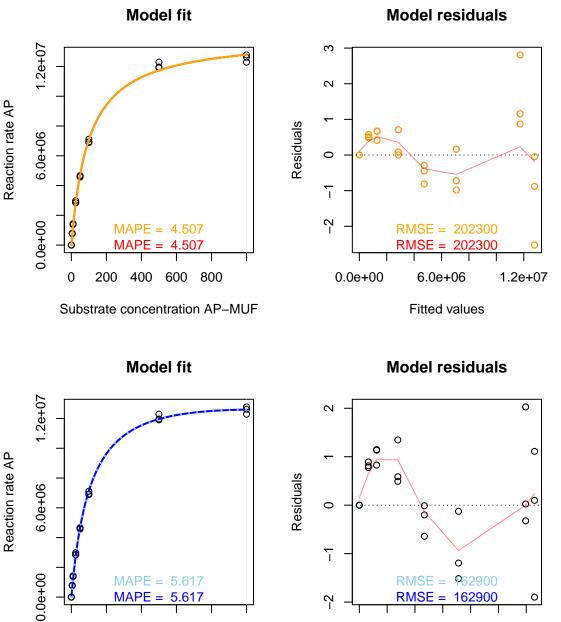












400

0

800

600

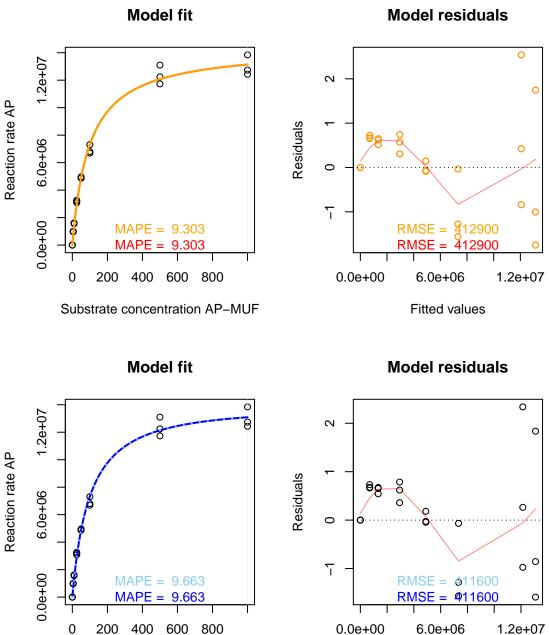
Substrate concentration AP-MUF

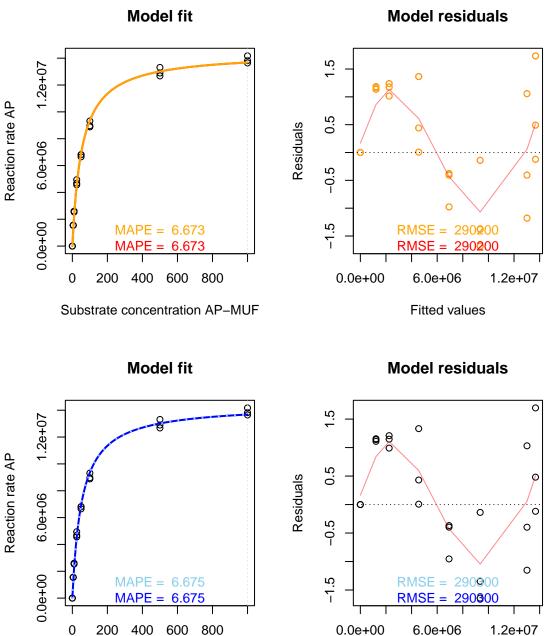
0.0e+00

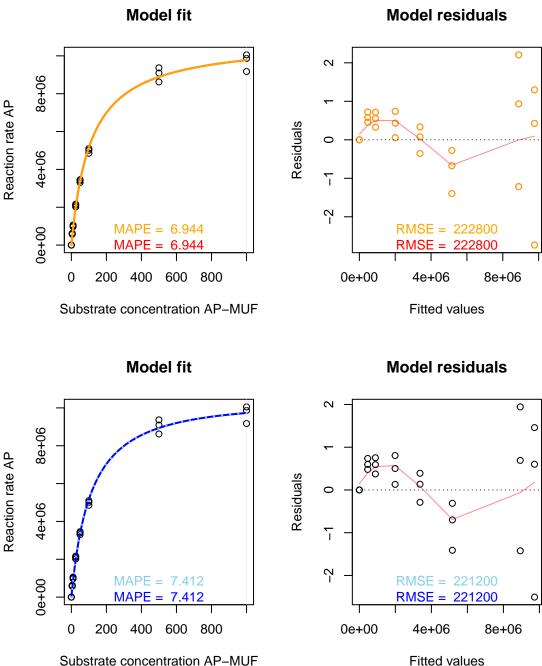
6.0e+06

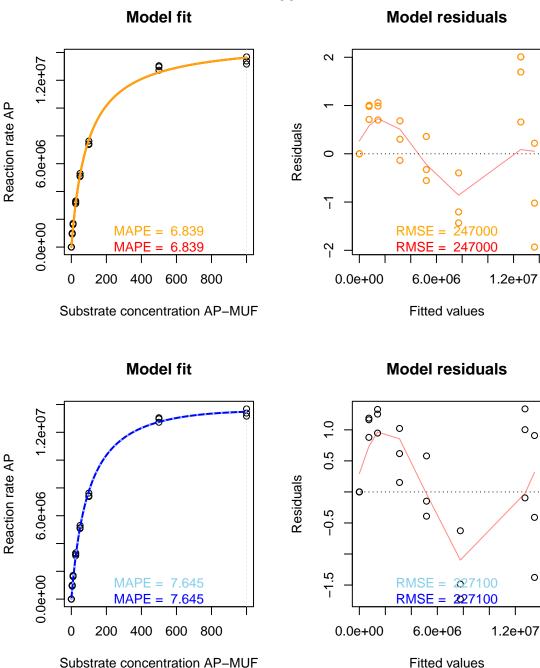
Fitted values

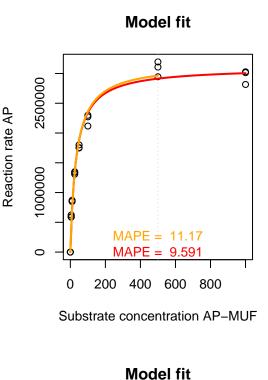
1.2e+07

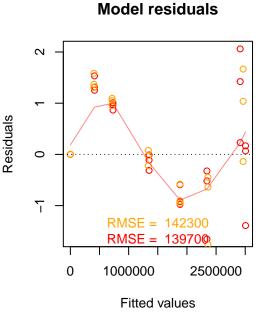


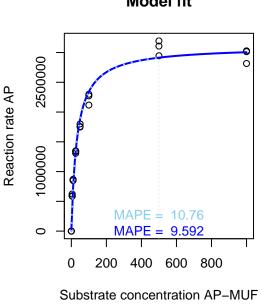


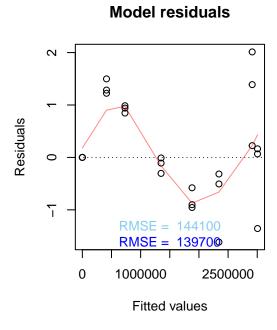


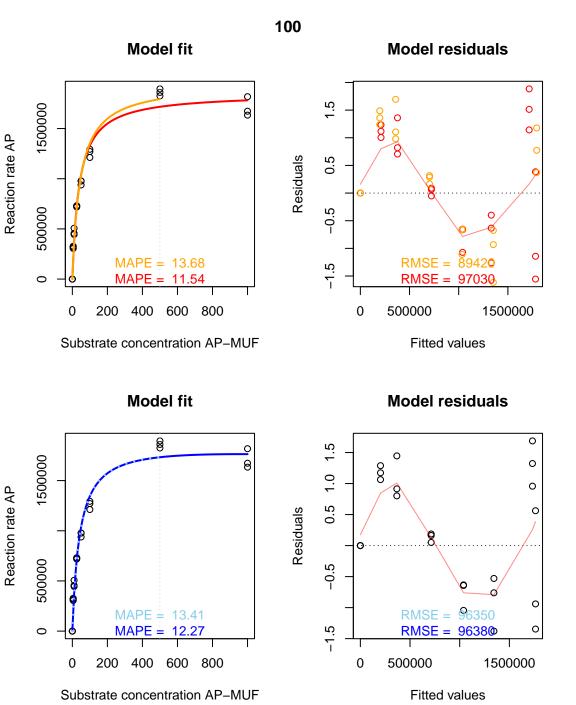




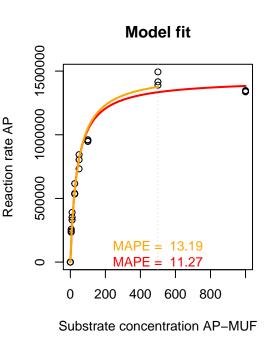


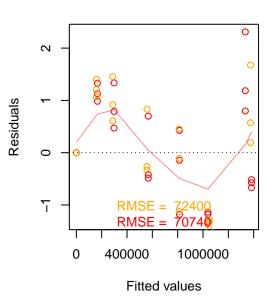




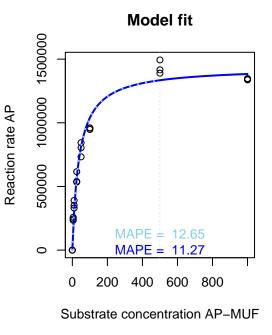


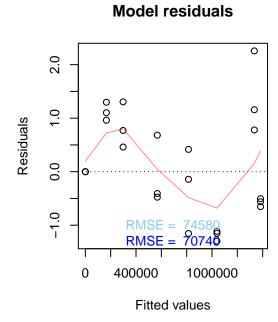


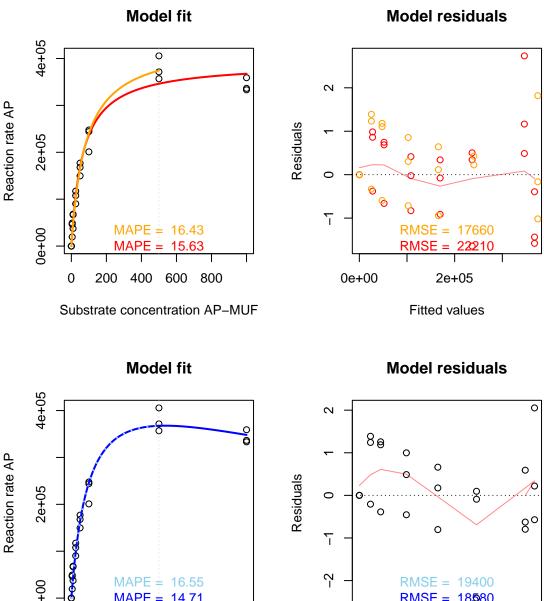




Model residuals







600

Substrate concentration AP-MUF

0

200

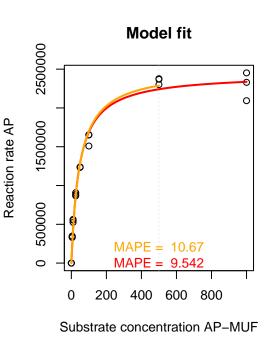
400

0e+00

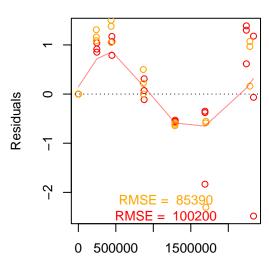
2e+05

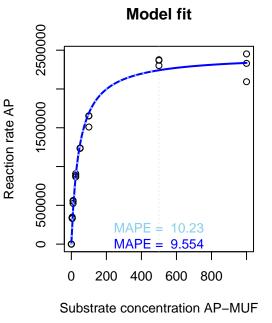
Fitted values





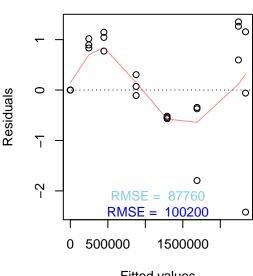
Model residuals



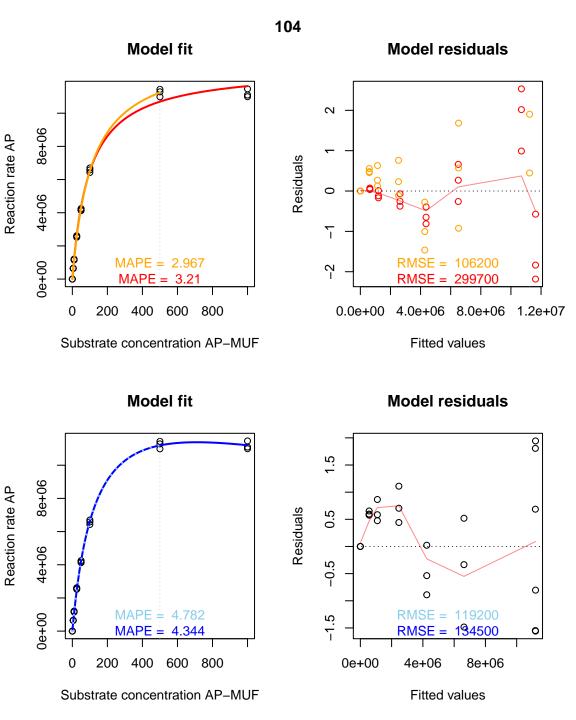


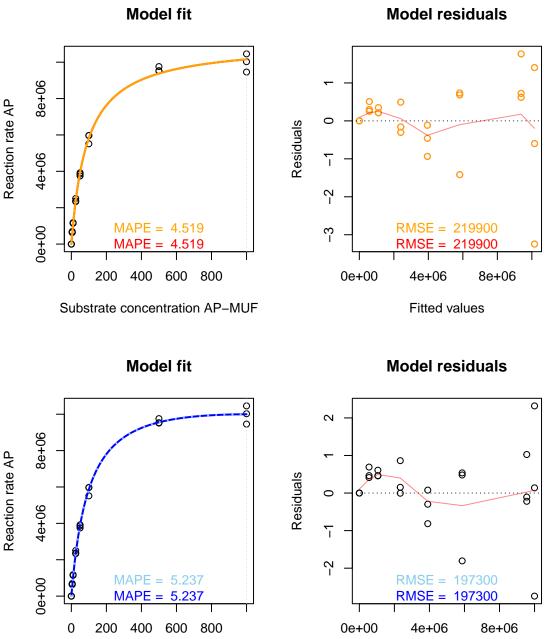
Model residuals

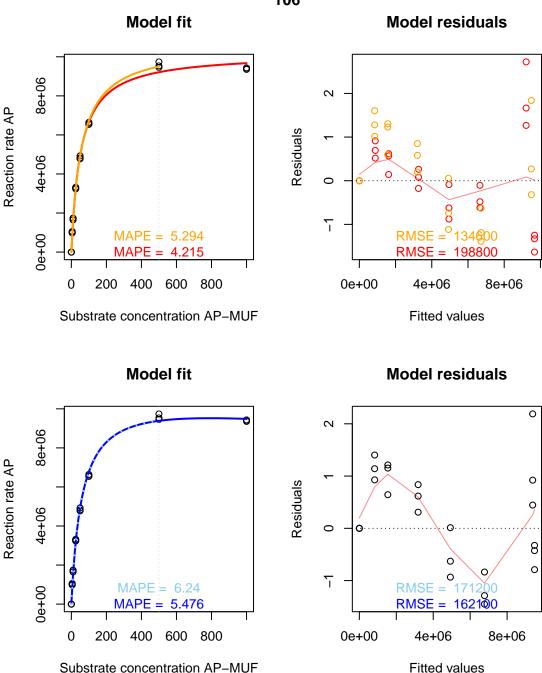
Fitted values

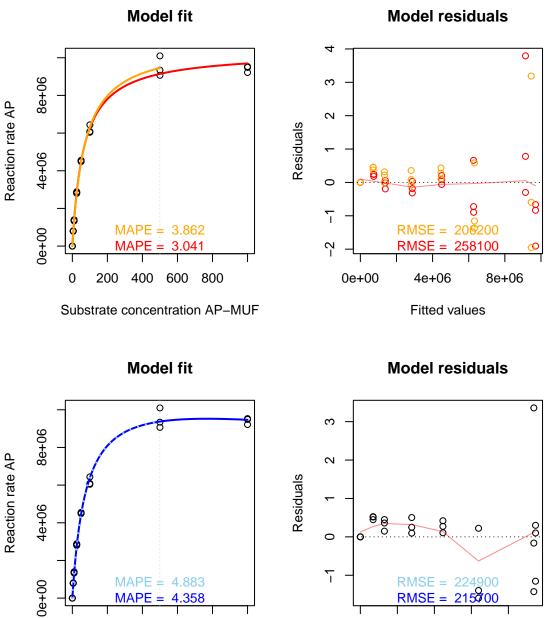


Fitted values









200

400

600

Substrate concentration AP-MUF

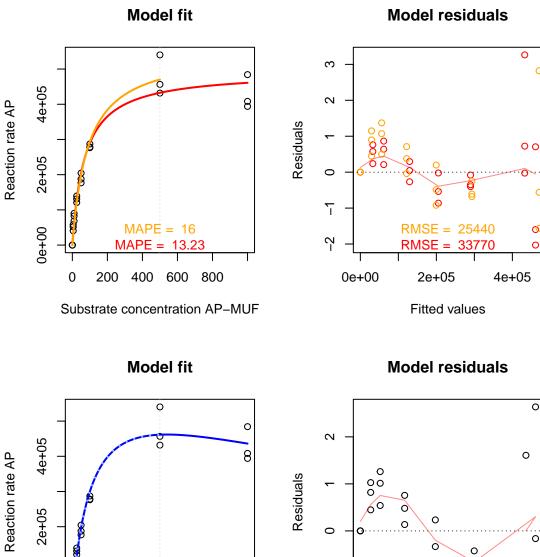
800

0e+00

4e+06

Fitted values

8e+06



MAPE = 18.31

Substrate concentration AP-MUF

600

800

400

200

0

0e+00

0

00

0

4e+05

0

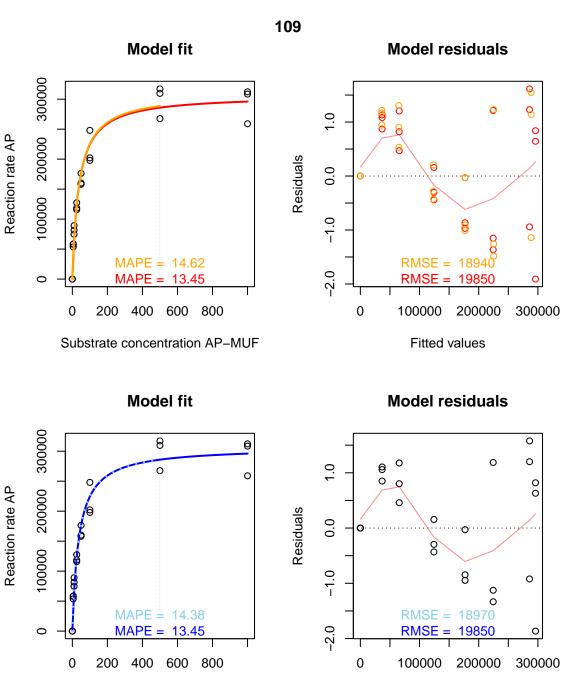
2e+05

Fitted values

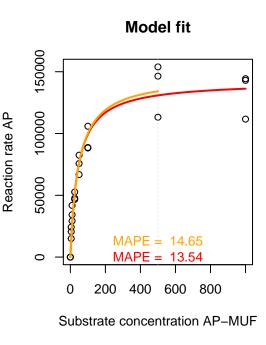
27830

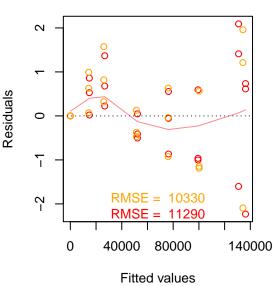
ī

0e+00

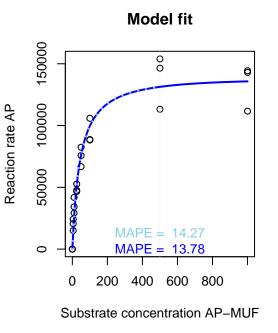


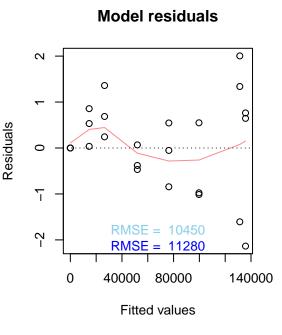


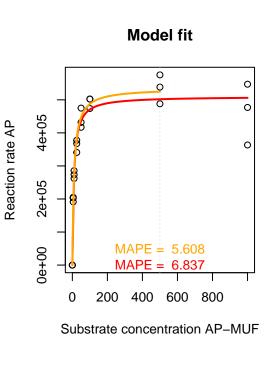




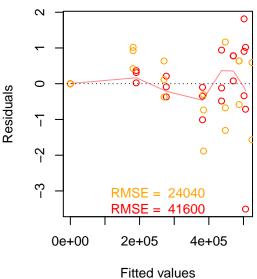
Model residuals



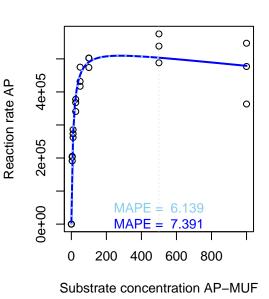




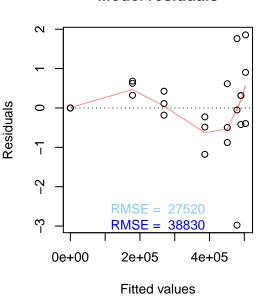




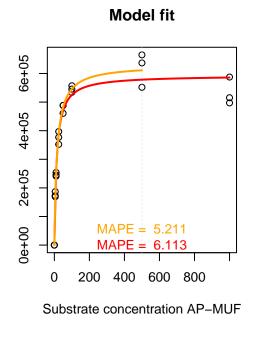




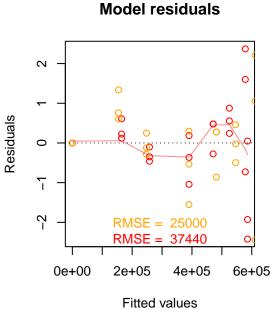
Model residuals

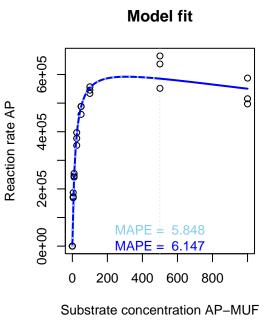


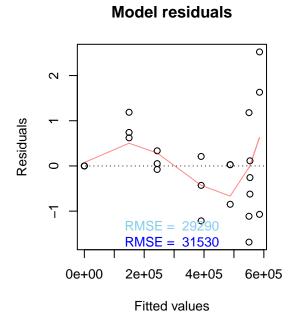


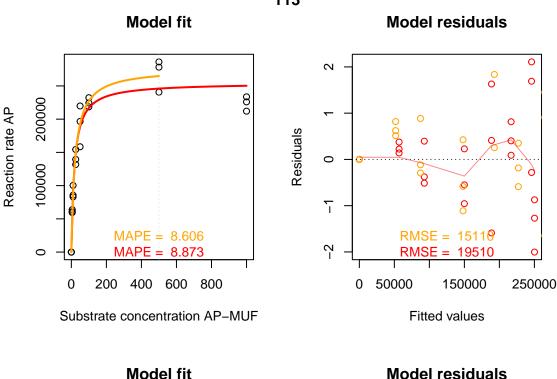


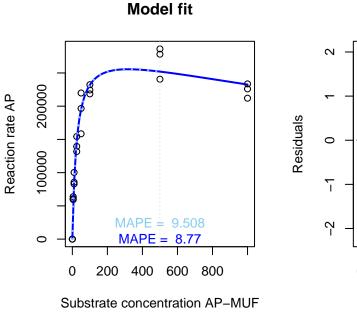
Reaction rate AP

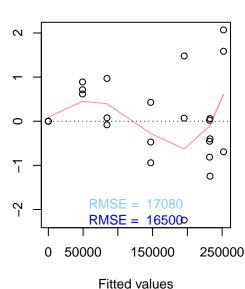


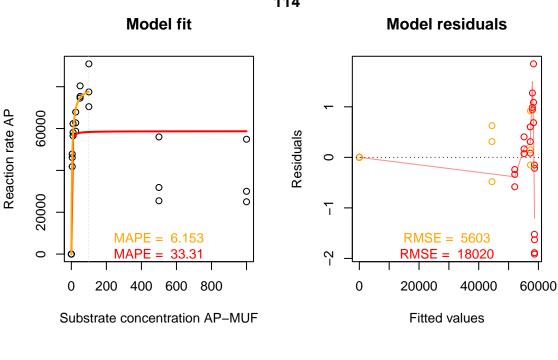


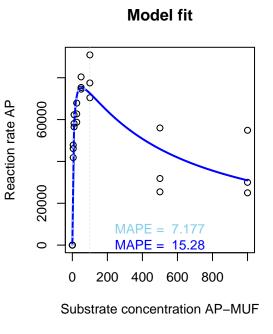


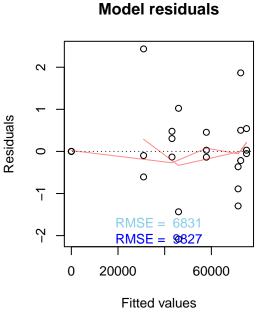


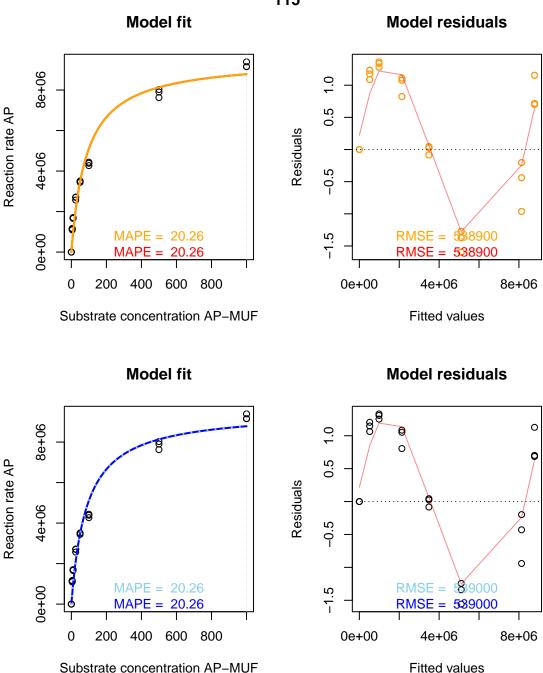


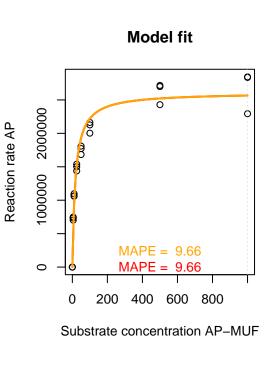


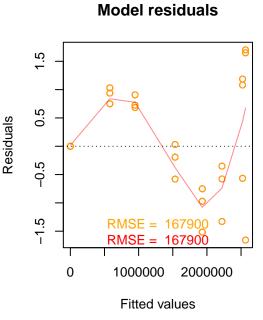


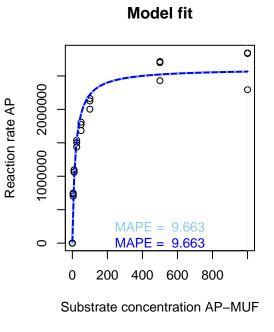


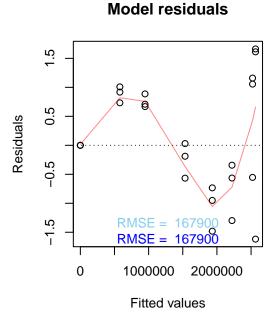


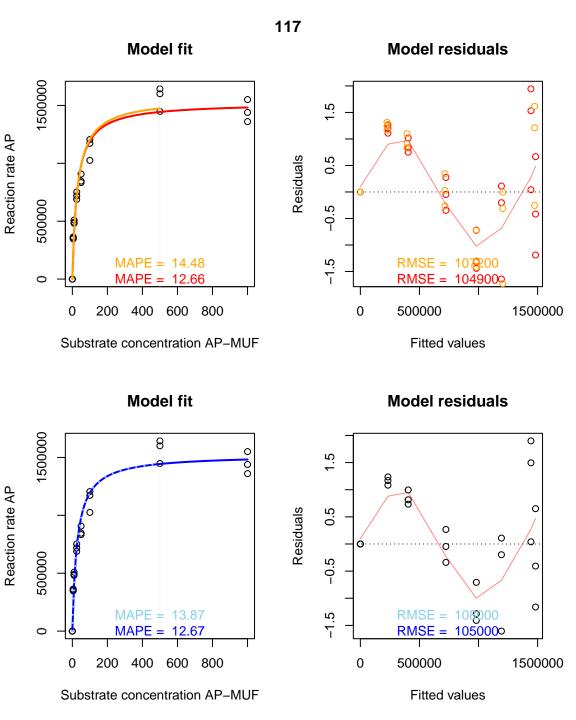


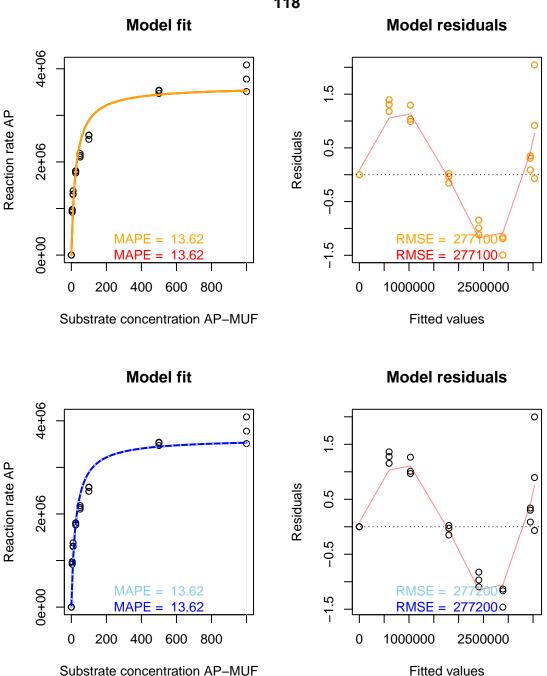


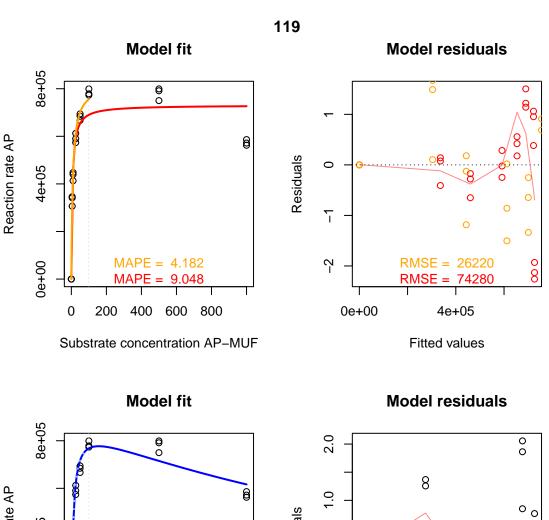


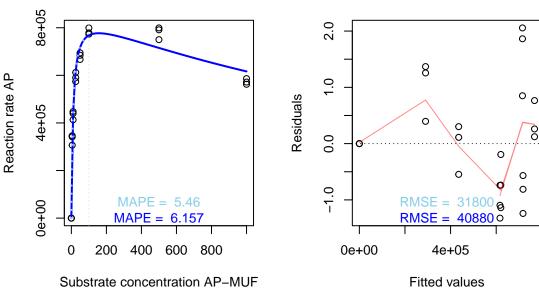


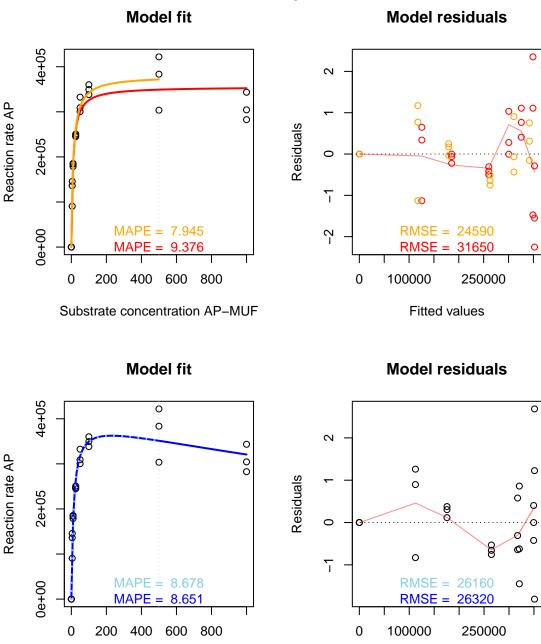






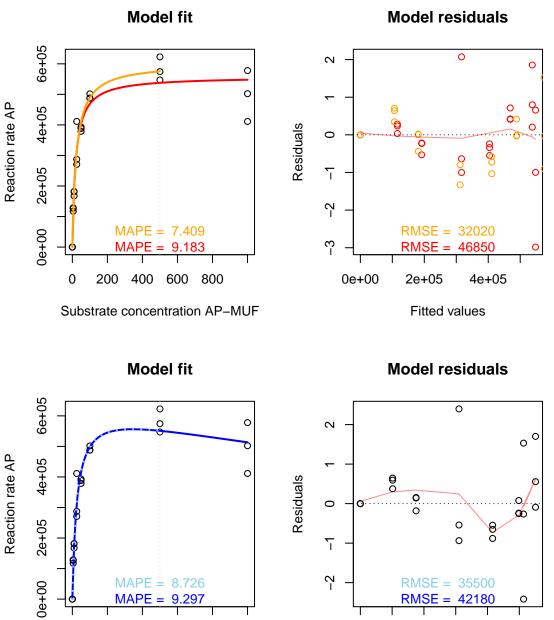






Fitted values

Substrate concentration AP-MUF



0e+00

2e+05

Fitted values

4e+05

Substrate concentration AP-MUF

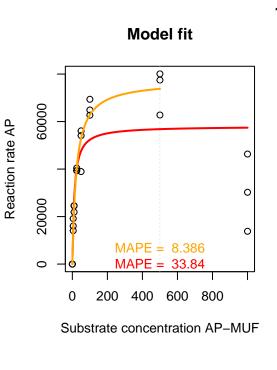
600

800

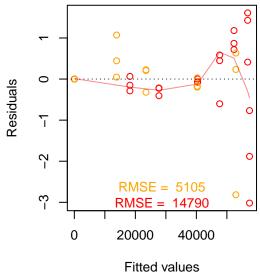
400

0

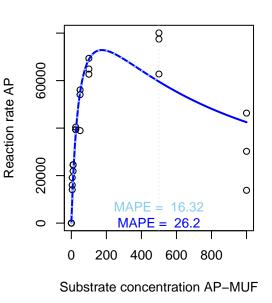
200







Model fit



Model residuals

